

Probing interfaces in magnetic nanolayers with soft x-ray standing waves

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- ***Introduction to techniques***
 - *X-ray optics and electron/x-ray emission processes in spectroscopy*
 - *Depth-resolved information using a standing wave generator (SWG)*
- ***Magnetic moments and magnetic order at buried interfaces in magnetic nanolayers: Cr/Fe***
 - *Cr and Fe 3s high-resolution photoemission: local magnetic moment*
 - *X-ray magnetic circular dichroism (XMCD) in Cr and Fe 2p and 3p photoemission : magnetic order*
- ***Conclusion and future work***

*Why study **interfaces** in magnetic multilayers ?*

→ - **spin dependent scattering of electrons at interface**
magnetic anisotropy, exchange bias near interface
® **GMR, MTJ, TMR, spin valve,...**

→ - **chemical & magnetic variation at interface**

Fe/Cr : giant MR (Fe: F, Cr: AF)
MR > 40 % at T=4.5 K and 10 % at T=300 K

Some questions :

- **degree of interdiffusion at interfaces**
- **chemical and magnetic variation or roughnesses**
- **distribution of magnetic order
and magnetic moment near interface**
(A. Fujimori et al; C. Turtur et al.)

→ **to be discussed here**

→ **ongoing or future project**

Specific projects (Berkeley, Oct. 1998 – present)

-*general consideration of full x-ray optics and electron emission processes in spectroscopy*

® *first-of-its-kind C program, all effects included > 5K lines
(to be submitted to Phys. Rev. B)*

→ -*novel uses of multilayer standing wave generators (SWG)
in spectroscopy*

® *depth-resolved photoemission (Surf. Sci. Lett, 461 L557 (2000))*
® *non-destructive probing buried interface in magnetic
nanolayer (to be submitted to Science)*

- *multi-atom resonant photoemission (MARPE)*

® *detailed analysis of macroscopic x-ray optical view of MARPE
(Phys. Rev. B 63, 115119 (2001); to be submitted to Phys. Rev.
Lett.)*

Semi-infinite layer : bulk & surface

X-ray Optics : $h\nu_{inc}$

- optical constant

$$n(h\nu) = 1 - d(h\nu) + i b(h\nu)$$

(Henke, Gullikson, Davis)

scattering form factors f_1, f_2

- absorption, transmission

(Henke et al., Windt)

- variable x-ray polarization

(s, p, RCP, LCP and mixed)

Photoelectron emission : e

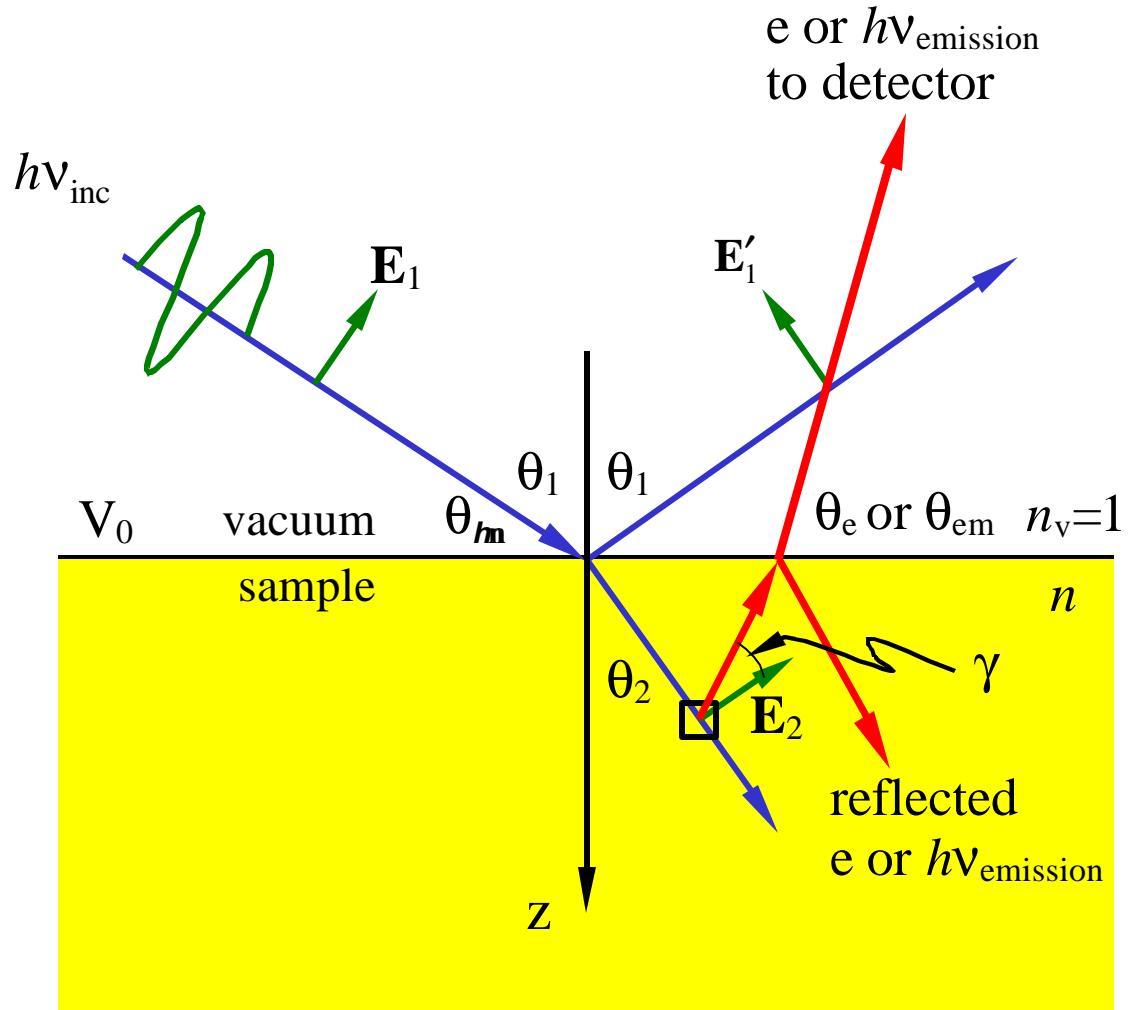
- atomic cross section (Yeh, Lindau)

- asymmetry factor (Fadley)

- electron inelastic attenuation (Tanuma, et al)

- reflection & refraction of electron at surface (Fadley)

X-ray emission : $h\nu_{emission}$



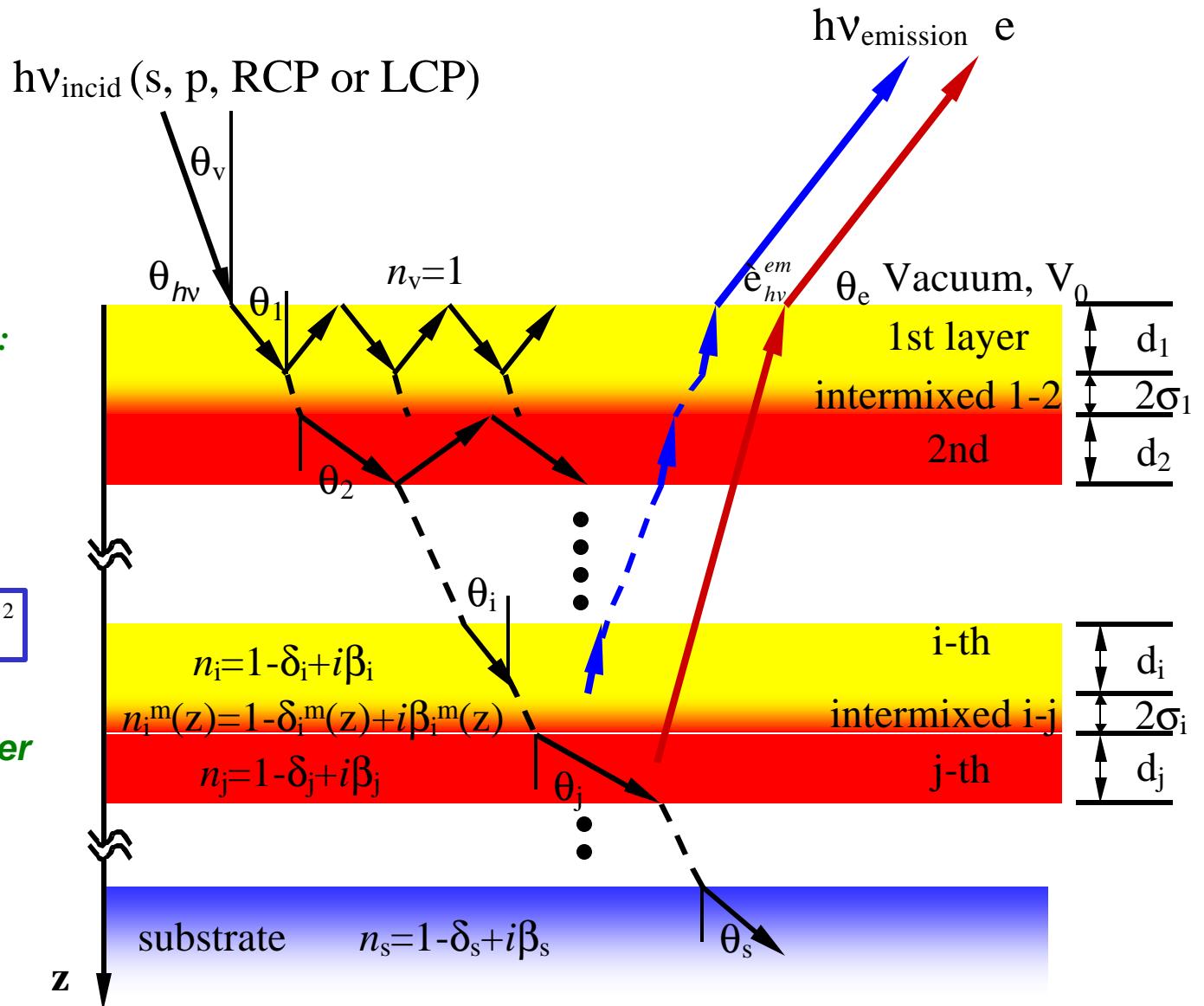
Multilayer : Standing Wave Generator

Calculations :

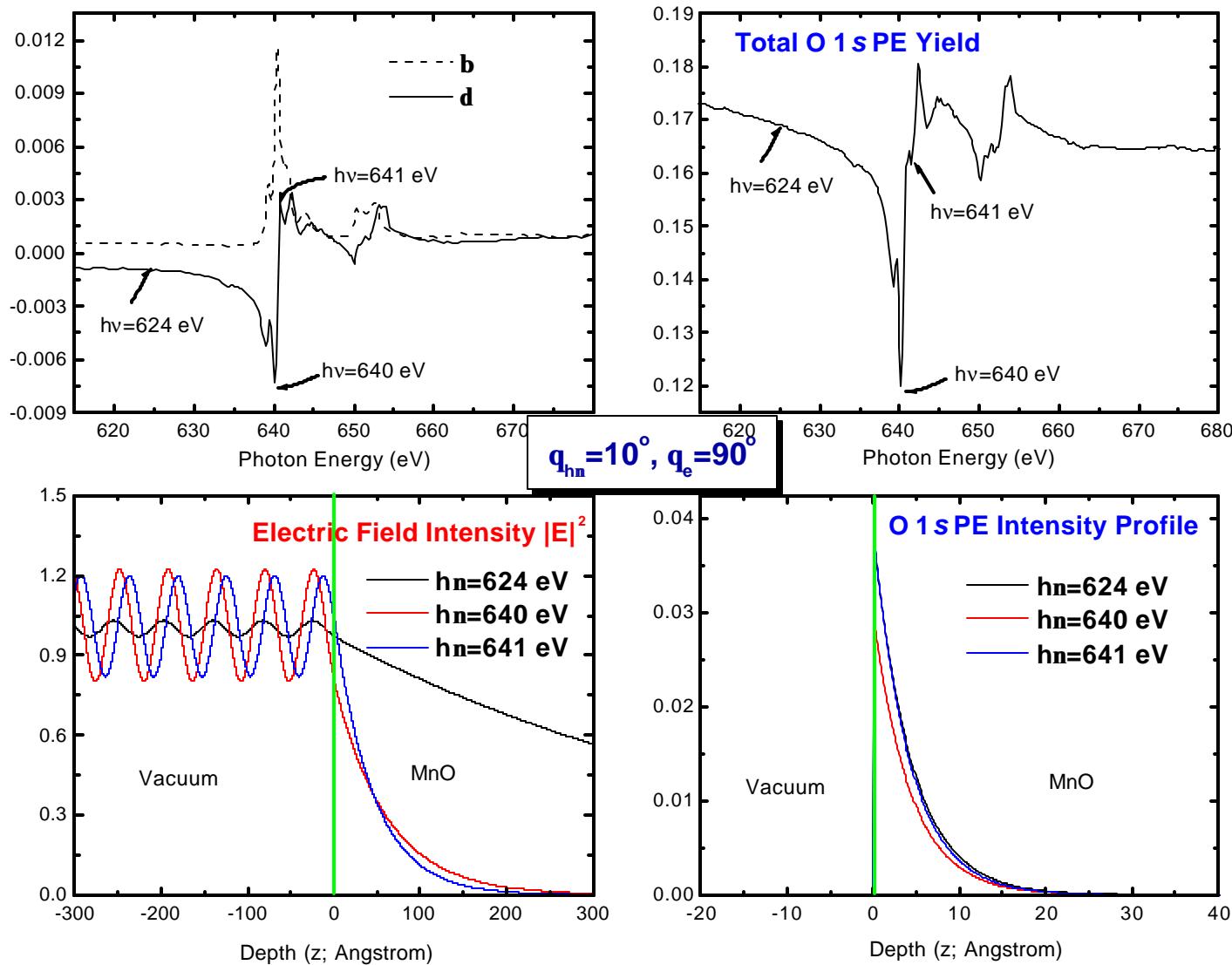
- multiple reflection & refraction
- intermixing ($s_i(z)$) : exact numerical treatment of interface diffusion profile

$$I_i(z) = |\mathbf{E}_i^+(z) + \mathbf{E}_i^-(z)|^2$$

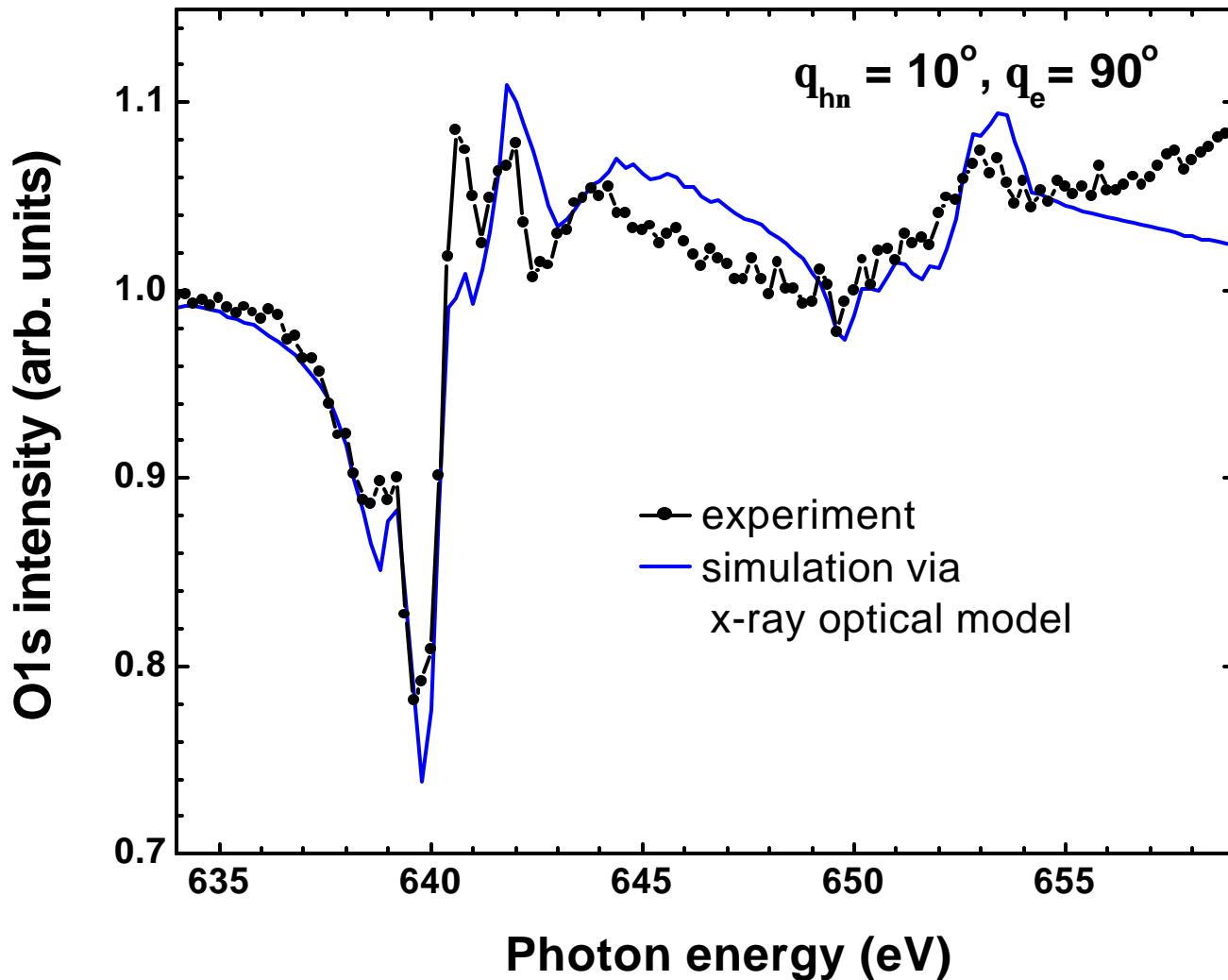
= electric field intensity at i -th layer (cf. Windt)



**A simple test : O 1s photoemission yield
from semi-infinite MnO around Mn 2p edges**

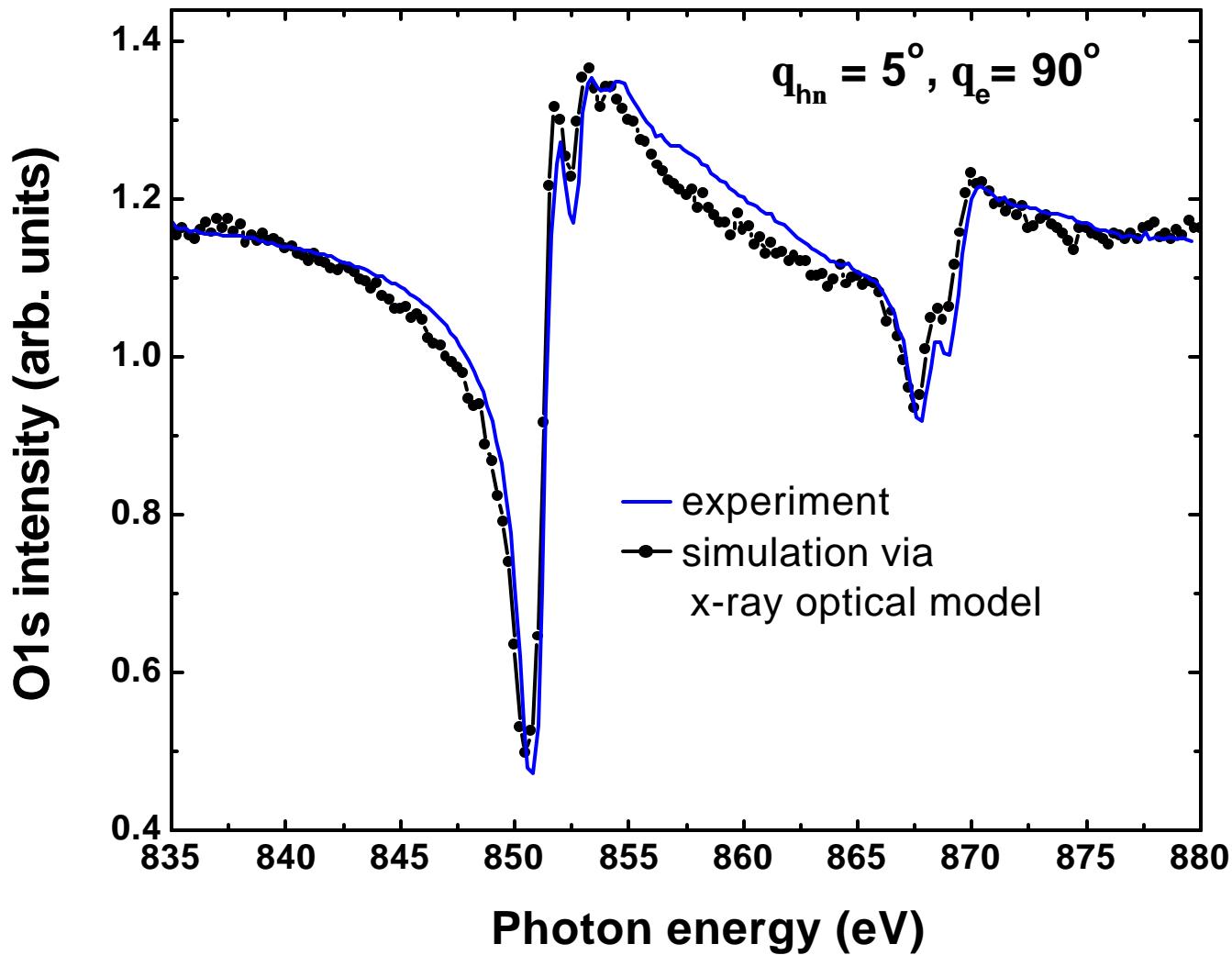


O 1s modulation around Mn 2p edge in MnO(001)



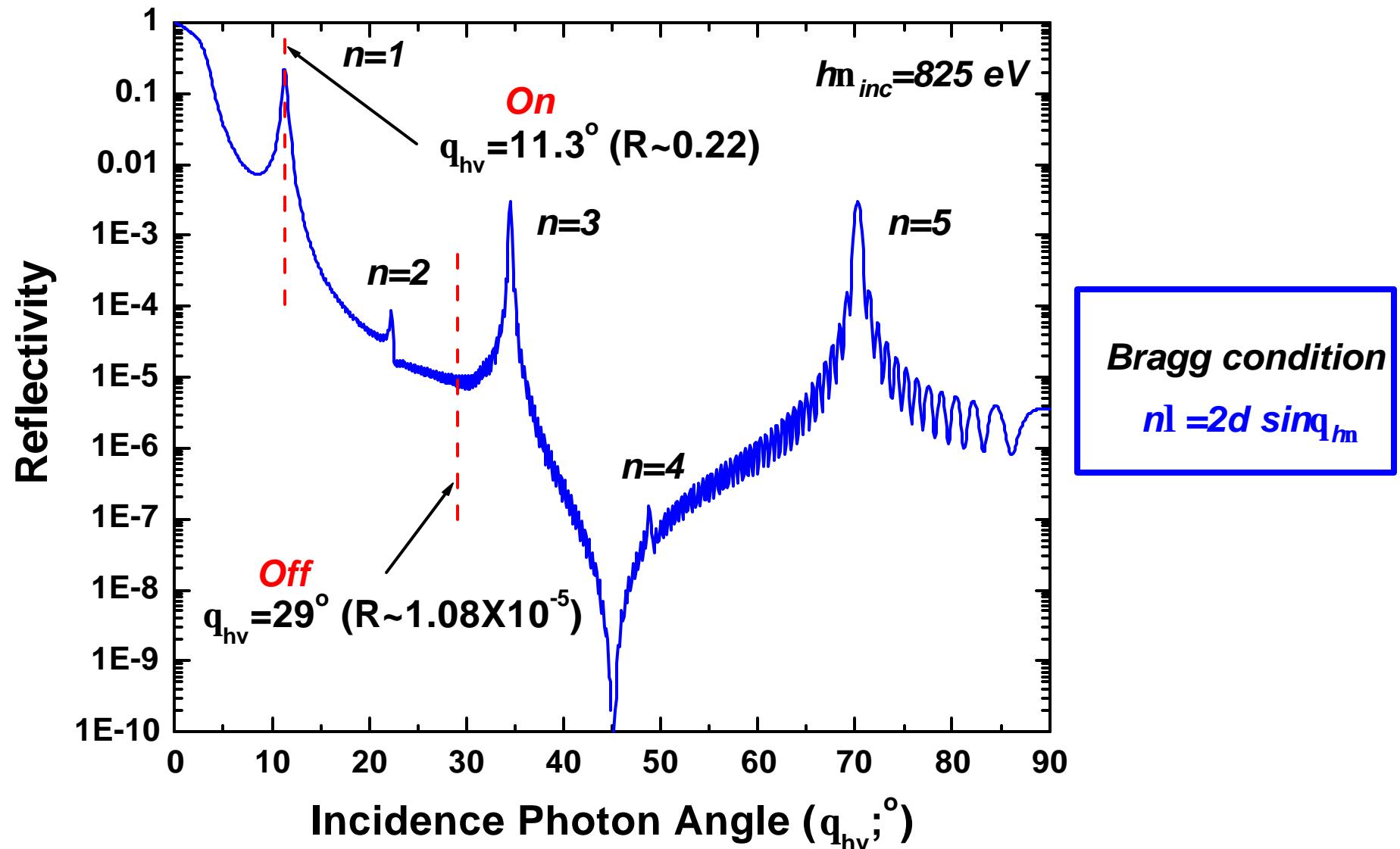
A. W. Kay, F. J. Garcia de Abajo, S.-H. Yang, et al
Phys. Rev. B 63 115119 (2001)

O 1s modulation around Ni 2p edge in NiO(001)

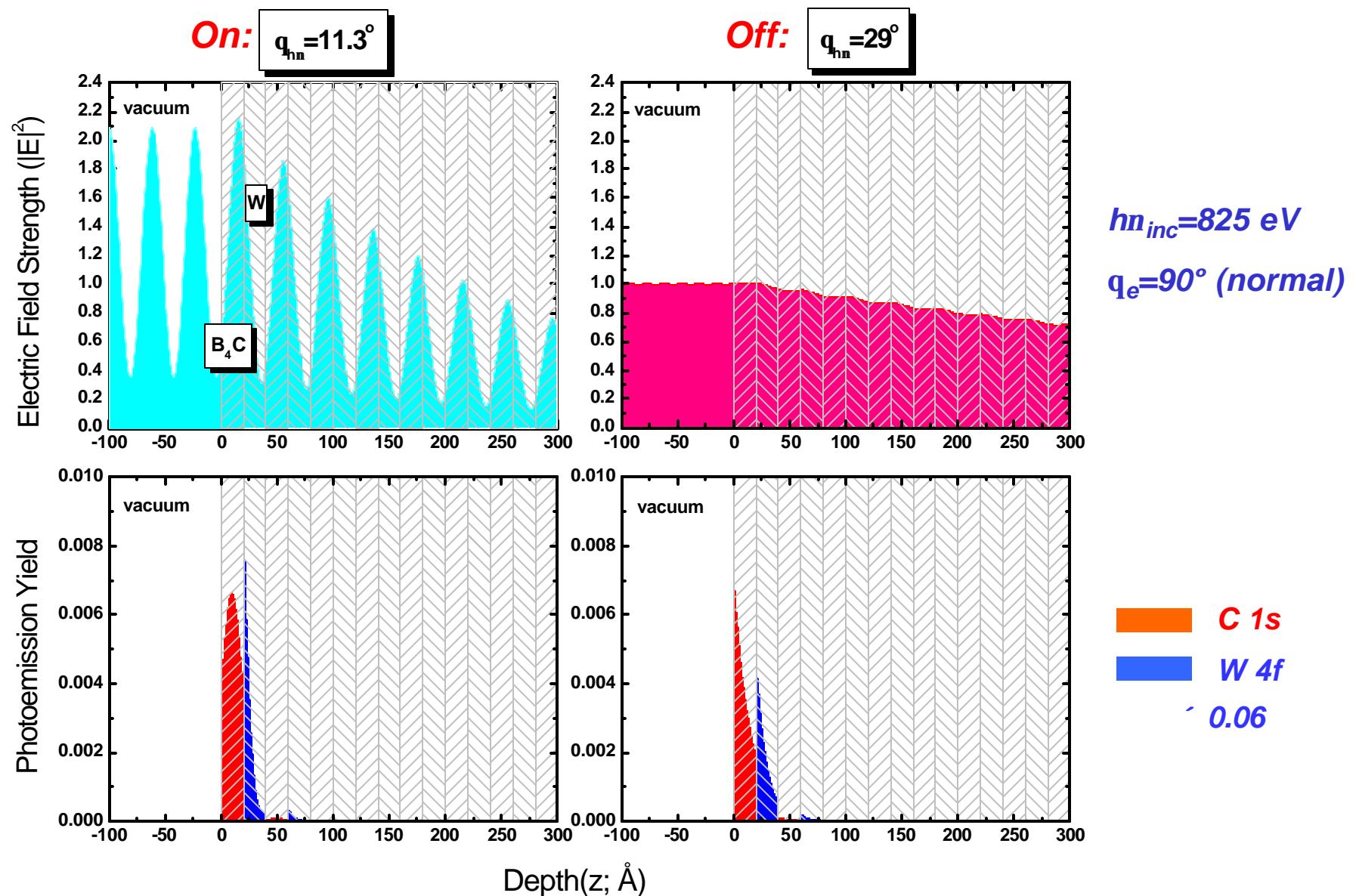


*N. Mannella, S.-H. Yang, L. Zhao, B. S. Mun, et al.
to be submitted to Phys. Rev. Lett.*

Multilayer reflectivity : $[B_4C$ (20 Å) /W (20 Å)]₂₀/Si

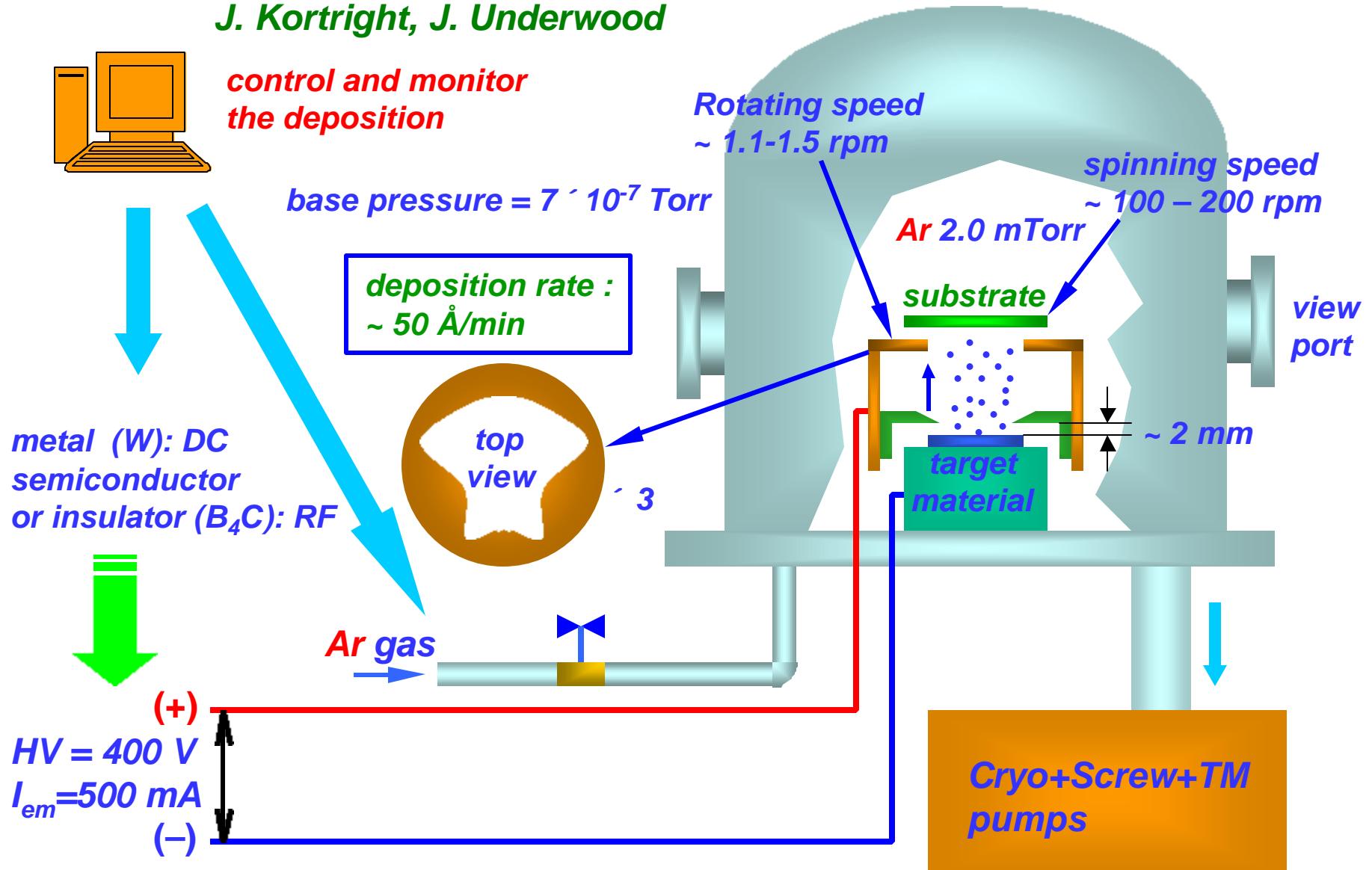


$[B_4C\text{ (20 \AA)}/W\text{ (20 \AA)}]_{20}/Si$

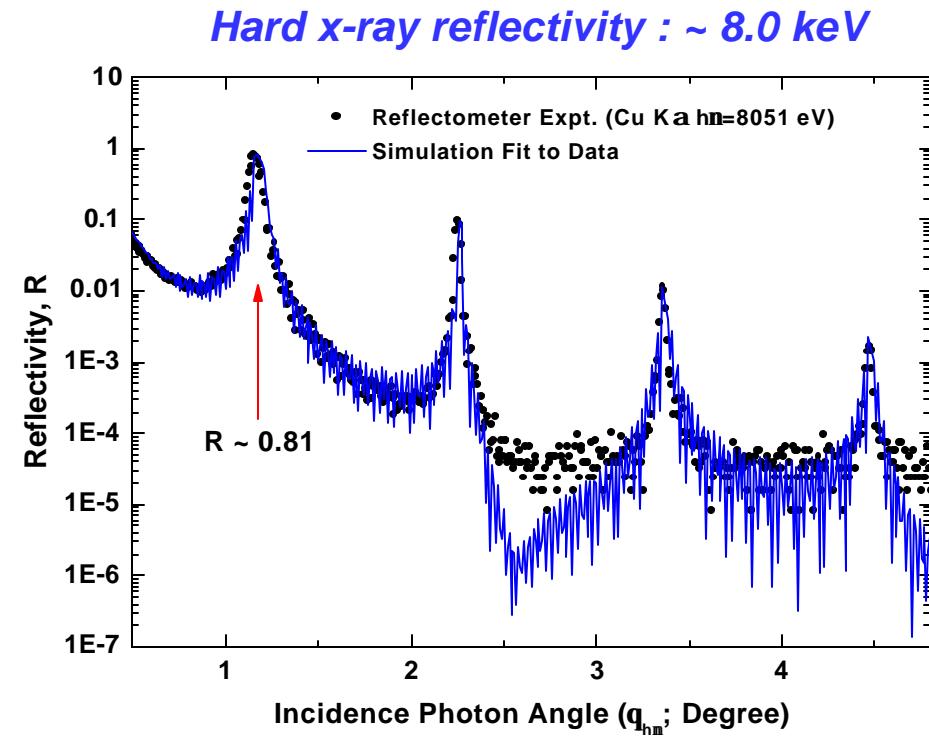
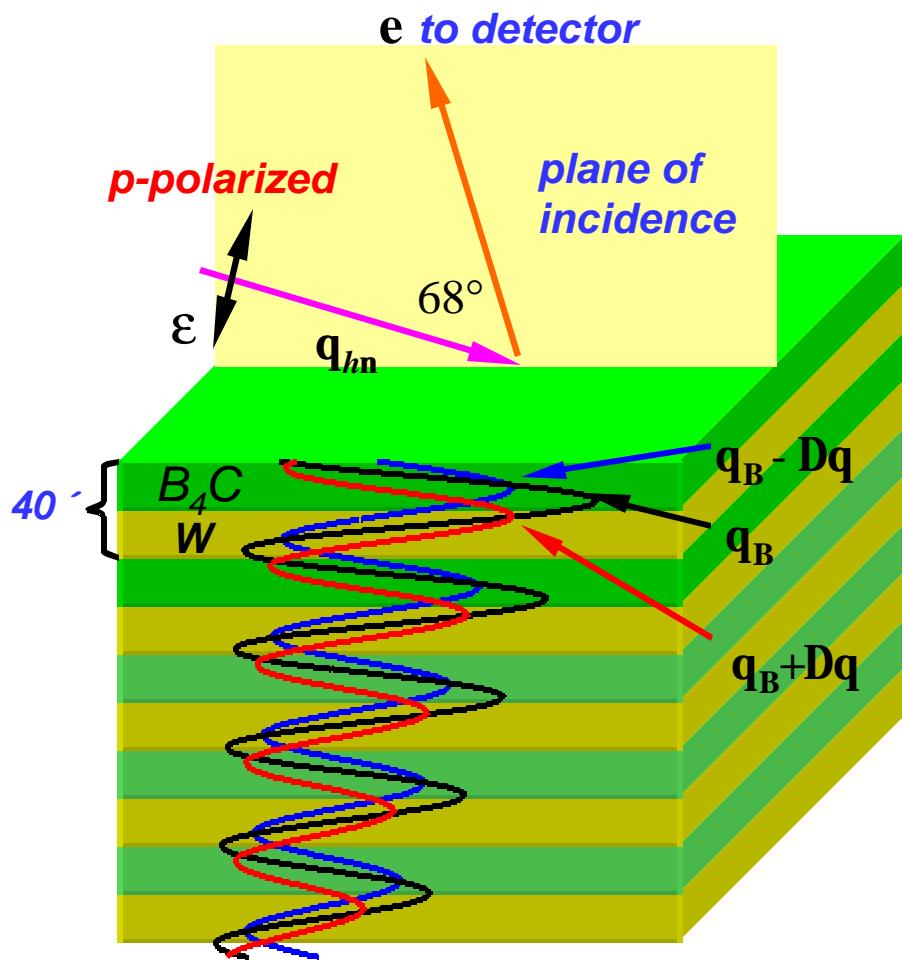


Sputter Chamber for Multilayer Growth

Center for X-ray Optics (CXRO):
J. Kortright, J. Underwood



Multilayer Soft X-ray Standing Wave Generator (SWG)



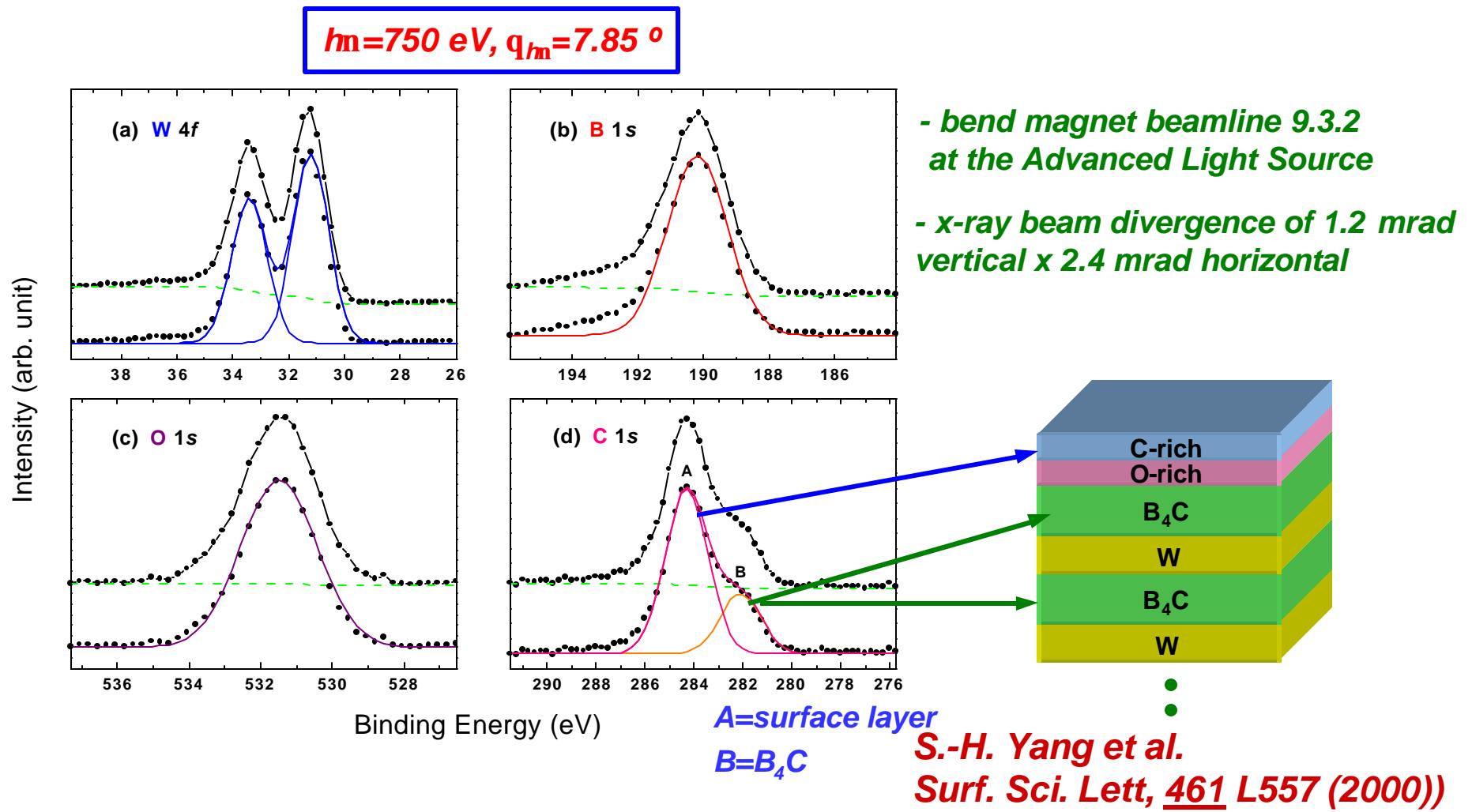
- light bake *in situ* (~ 70 °C), no other cleaning
- period = 39.6 Å, $[B_4C(22.5\text{ \AA})/W(17.1\text{ \AA})]_{40}$ on $SiO_2/polished Si(111)$
- interface diffusion length $s = 2.4$ Å

Previous work on photoemission from a SWG

core XPS from [Mo/B₄C]₃₀, Hayashi et al., (Appl. Phys. Lett. 68, 1921 (1996))

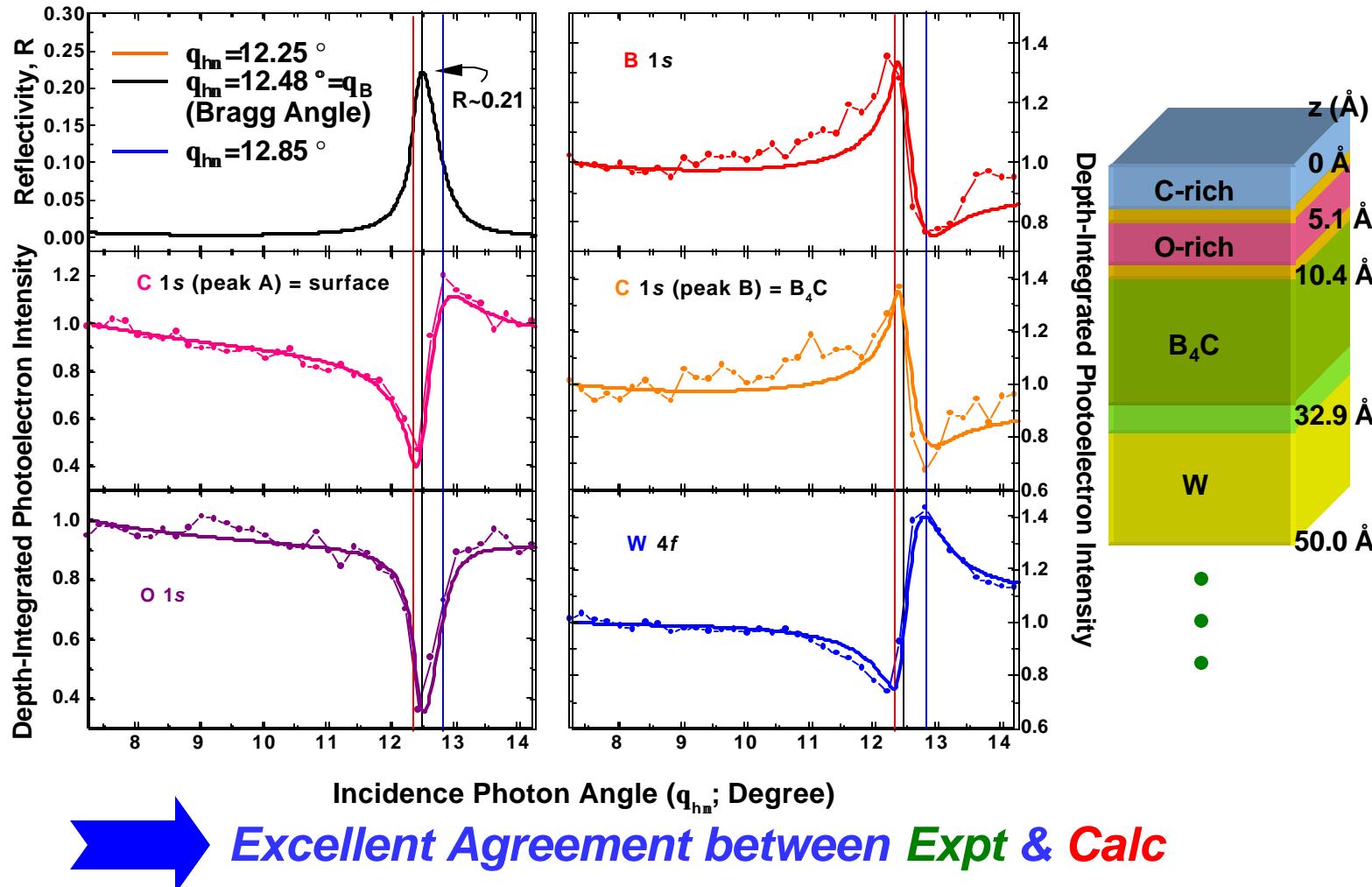
→ ~2.714 keV, unable to resolve unique behavior of different Mo, B and C peaks

Our work

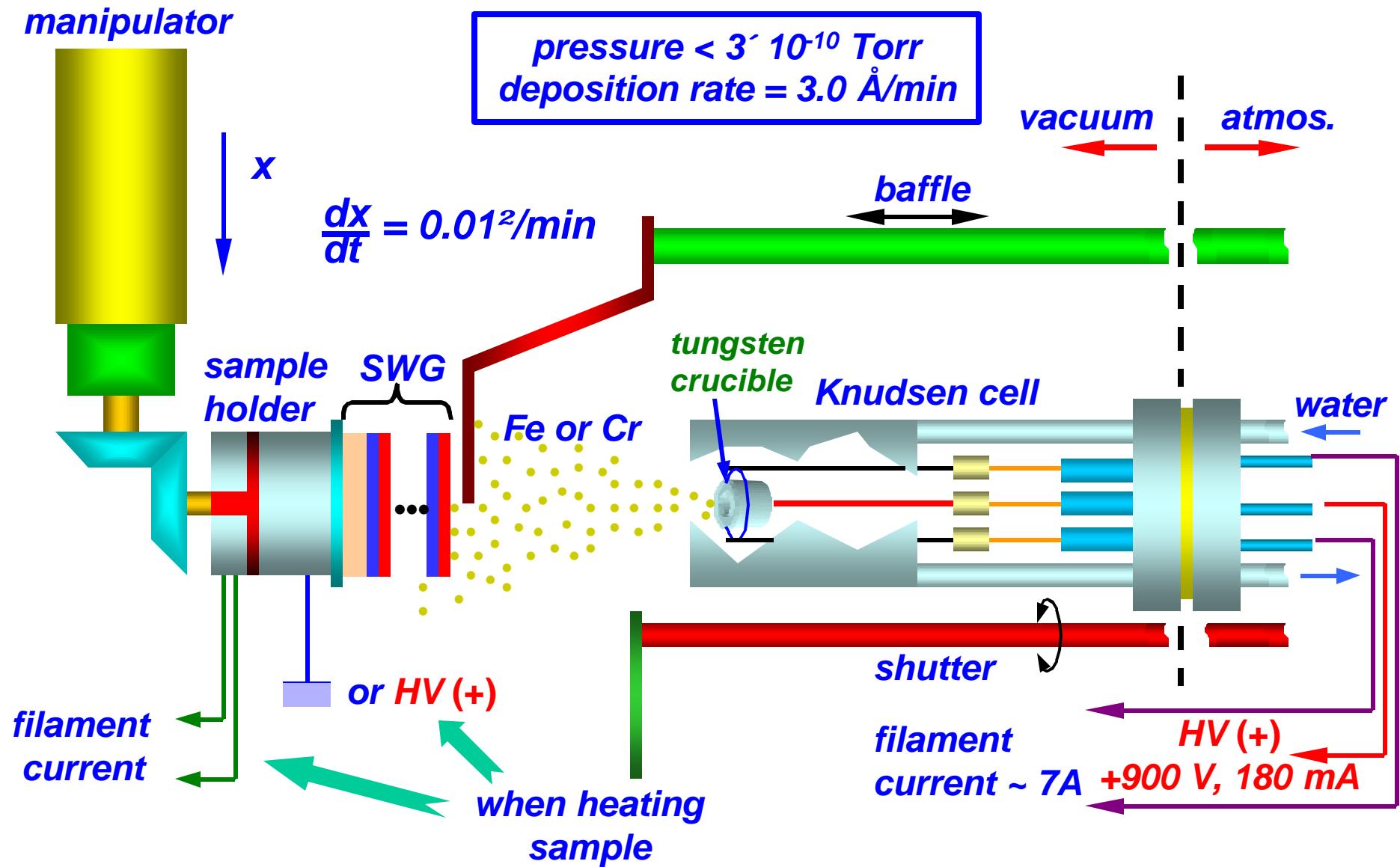


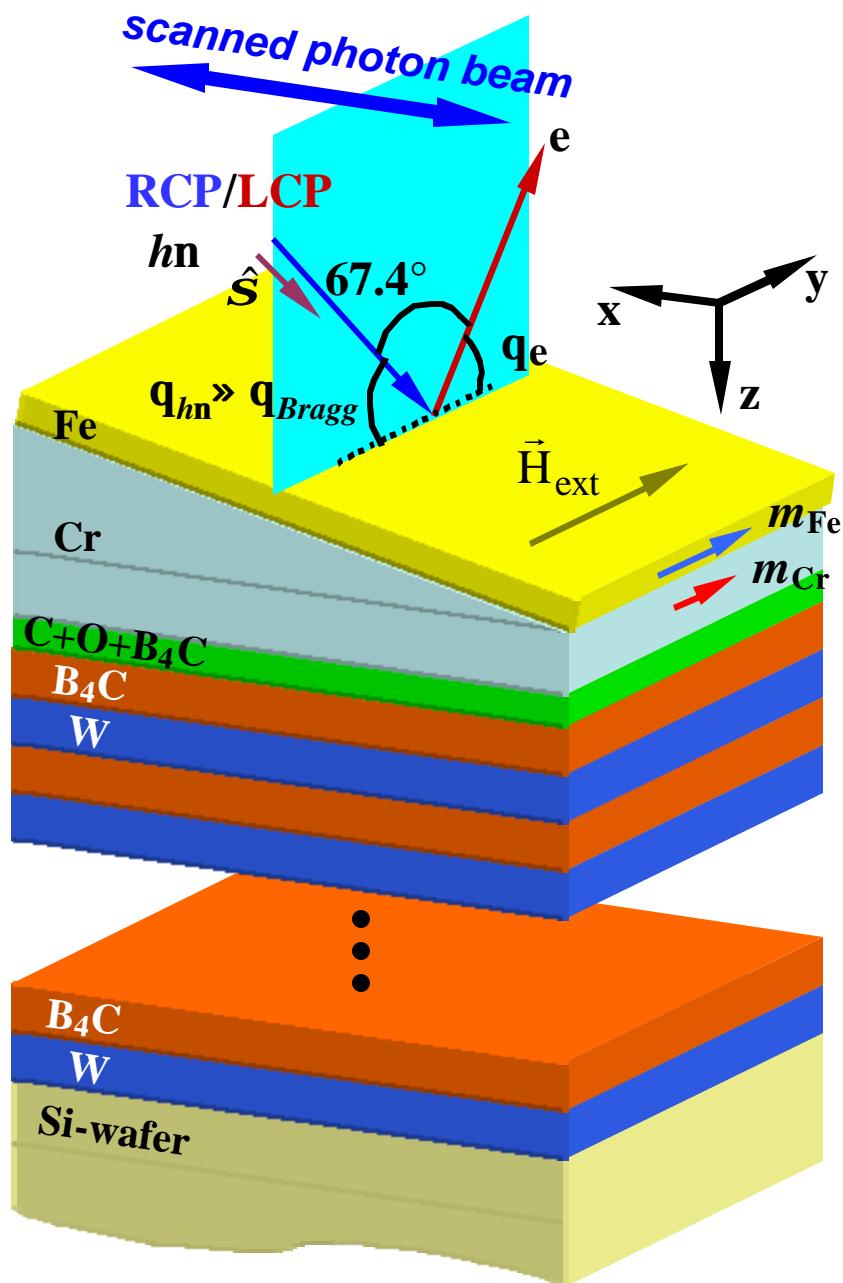
“Rocking curves” of photoemission yield for each core level

Experiment & Calculation → C-rich(5.1 Å)/O-rich(5.3 Å)/[B₄C(22.5 Å)/W(17.1 Å)]₄₀/SiO₂



In-situ MBE growth of Fe/Cr (wedge) bilayer on SWG





SWG :

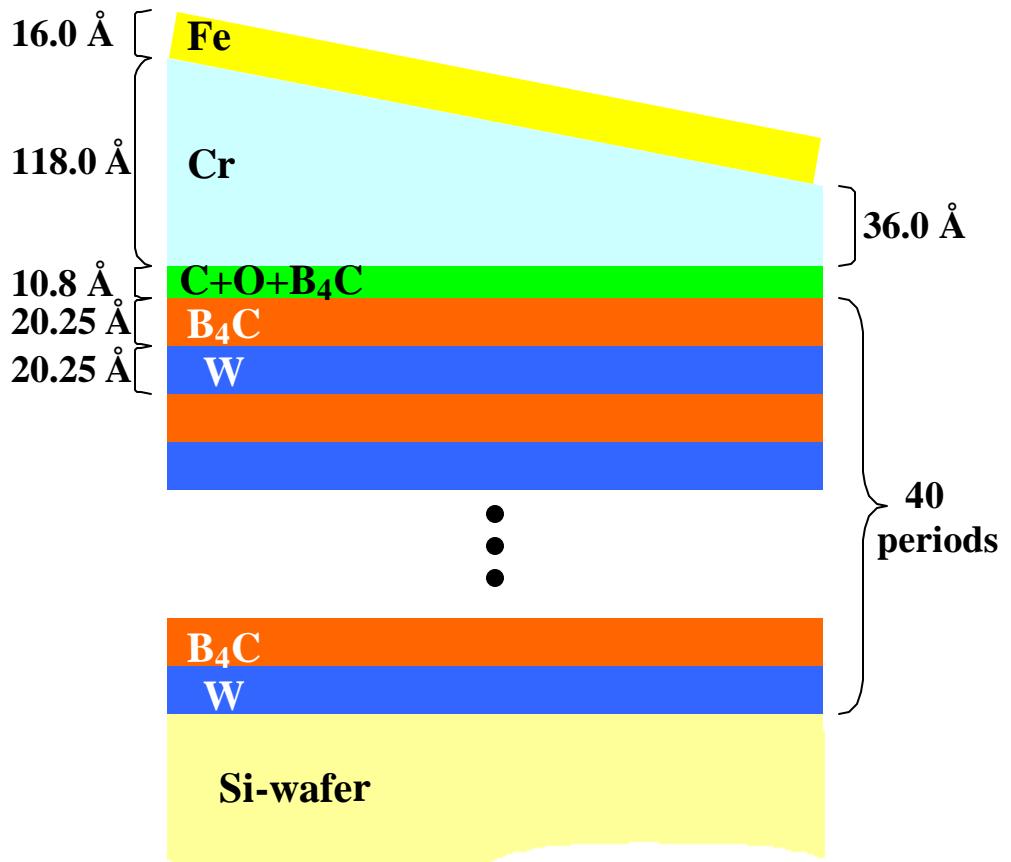
- period = 40.5 \AA , $[B_4C(20.25 \text{ \AA})/W(20.25 \text{ \AA})]_{40}$ on $\text{SiO}_2/\text{polished Si}(111)$

- reflectivity = $R = 71\%$ at $I_{hn} = 8.3 \text{ \AA}$ ($\text{Cu } K\alpha$)

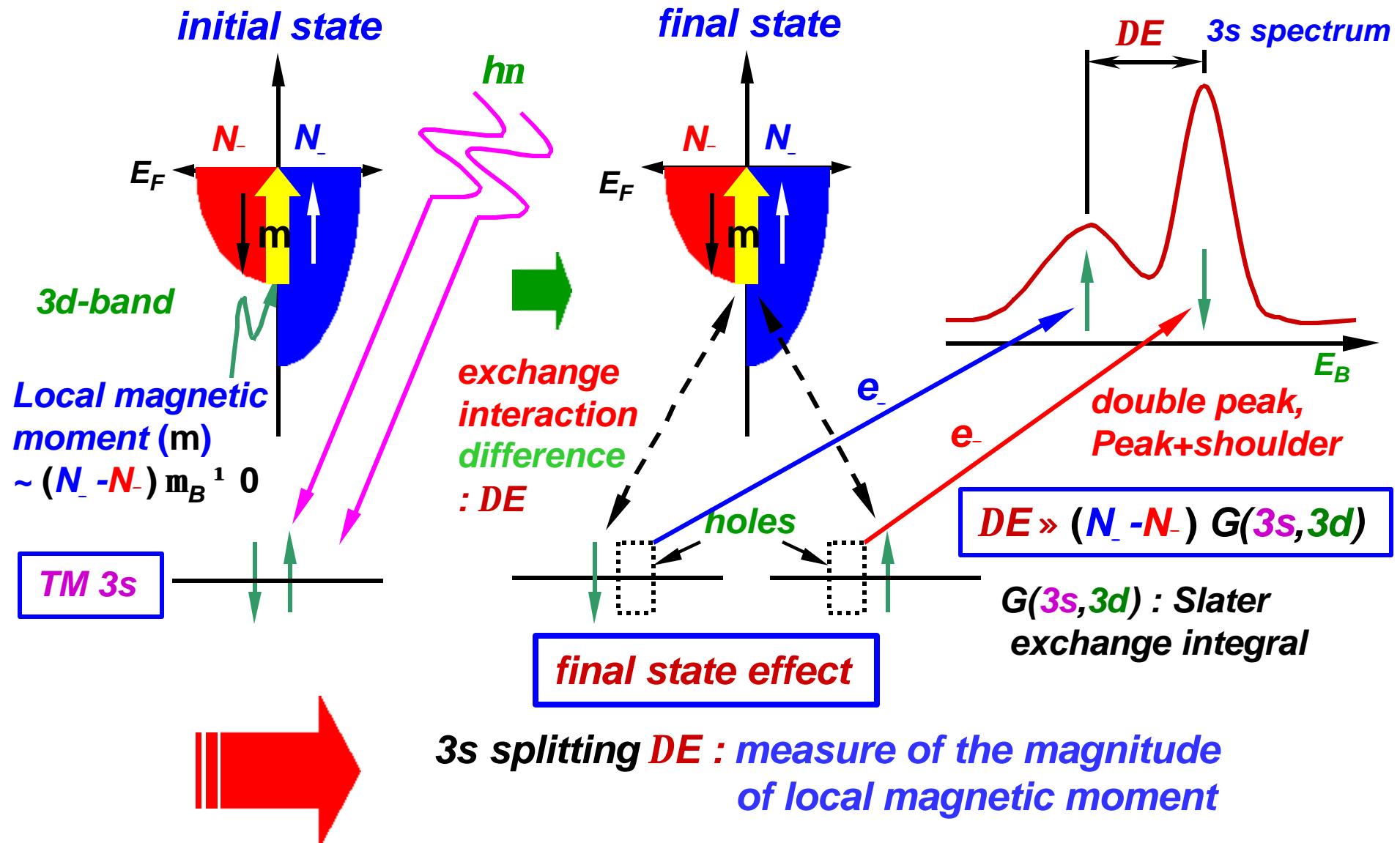
Fe/Cr bilayer :

- Fe: 16 \AA , Cr: $36 \sim 118 \text{ \AA}$

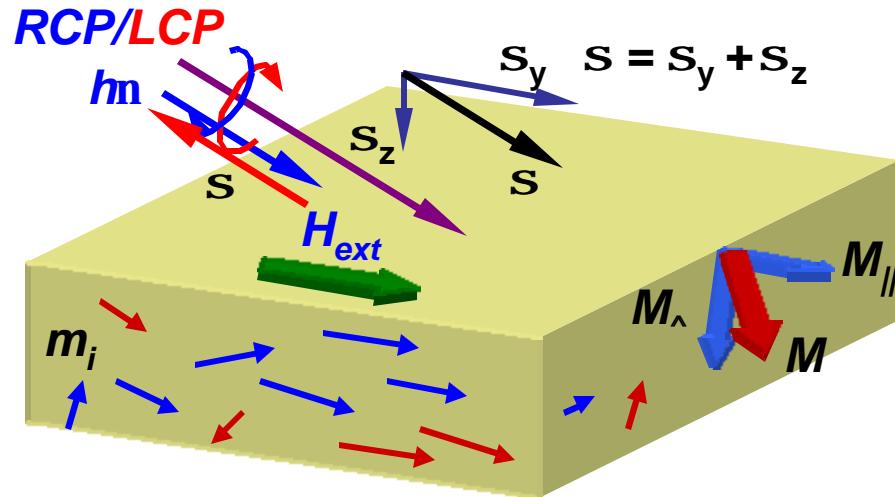
\dot{U} monitored by QCM and checked by simulation



3s spectrum for a magnetic 3d-transition metal



Magnetic Circular Dichroism (MCD) in Photoemission (PE)



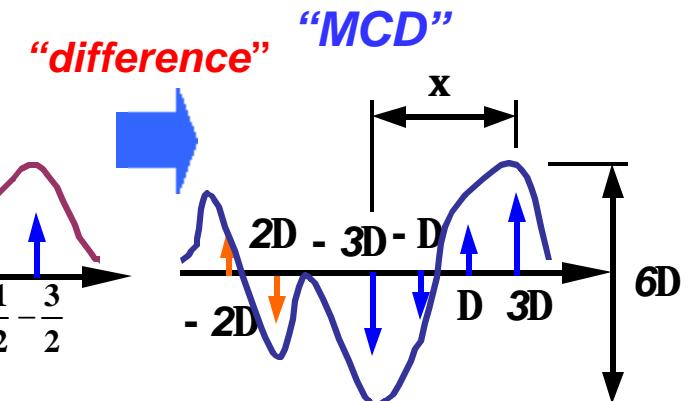
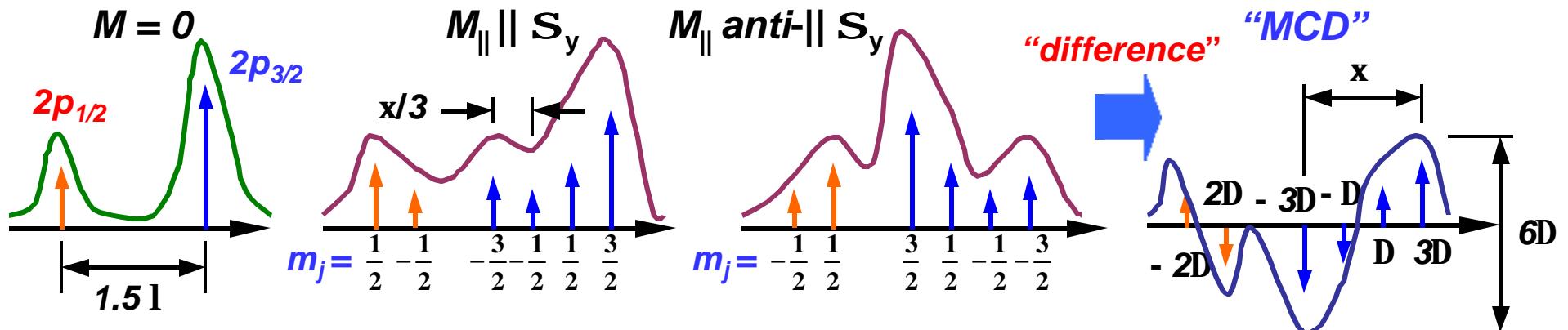
$$M = S_i \quad m_i = M_\parallel + M_\wedge$$

$$M_\parallel = M_y$$

$$M_\wedge = M_x + M_z = 0 \quad (\nabla H_{ext} \parallel y)$$

Hamiltonian

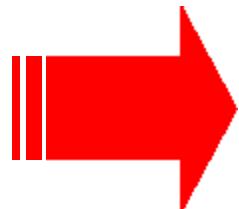
$$H = \mathbf{l} \cdot \mathbf{s} + xS_y$$



$$\text{MCD strength } \mu s \cdot S_i m_i = s_y M_\parallel$$

x or $6D$

$D \mu x$



MCD in PE : measure of ferromagnetic order along y -direction

Why MCD in photoemission and not in absorption?

Why is WEDGE crucial ?

- **Problems in X-ray absorption MCD of SWG**

A. optical properties are altered when photon energy is swept

B. SW's altered when incidence angle is scanned

{
Bragg angles change
Phases of SW change
Contrasts of SWG change

} as a function of
photon energy

→ **Too many free parameters to be determined --- see e. g.**
S. K. Kim and J. Kortright (LBNL), Phys. Rev. Lett, 86, 1347 (2001)

- **Our study**

- photoemission MCD solves problem A

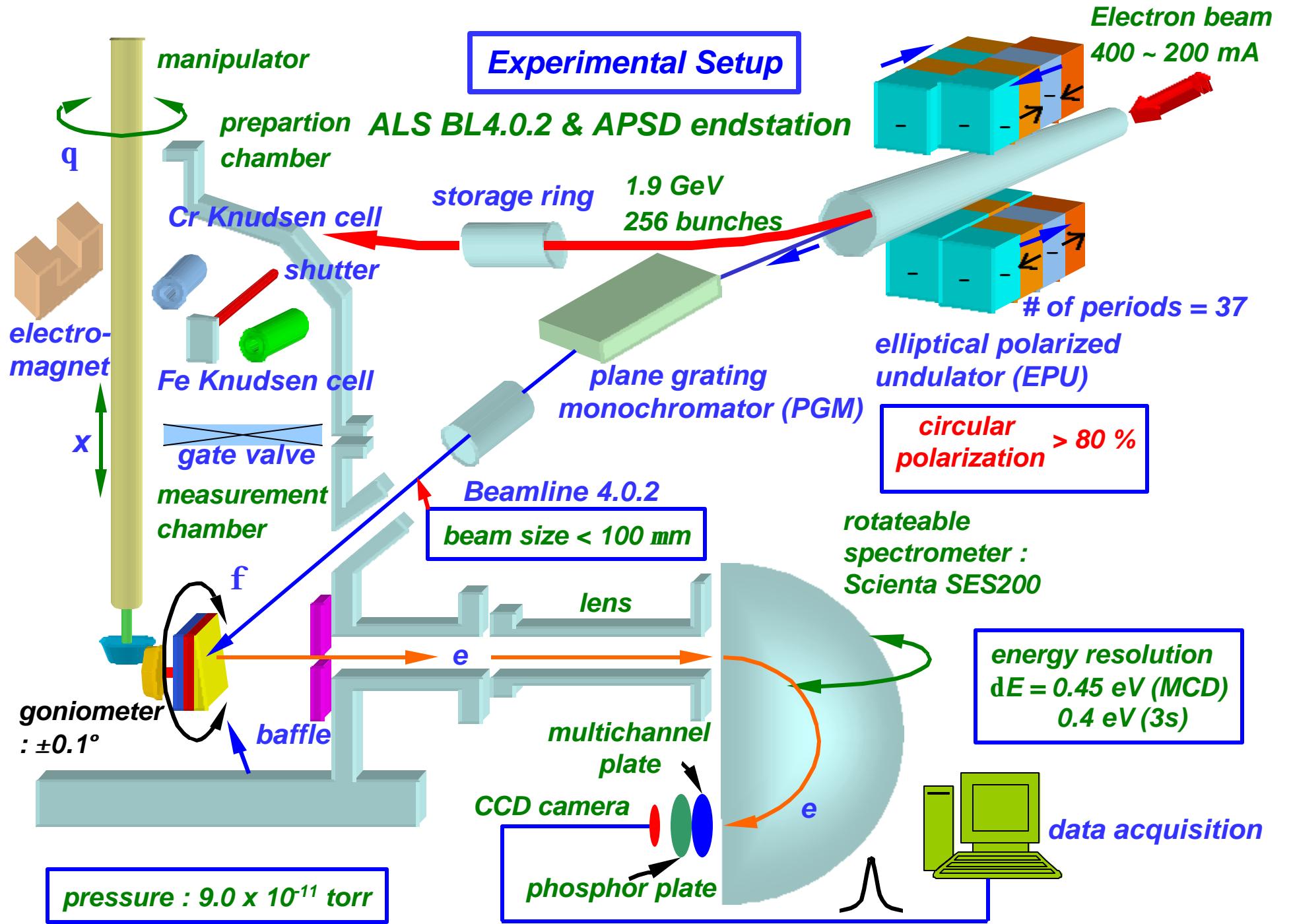
← **do not need to scan the photon energy; element-specific**

- wedge solves problems A and B

← **do not need to scan the incidence angle; phase pinning**



**This work : minimizes # of free parameters
improves depth-resolution of SW**

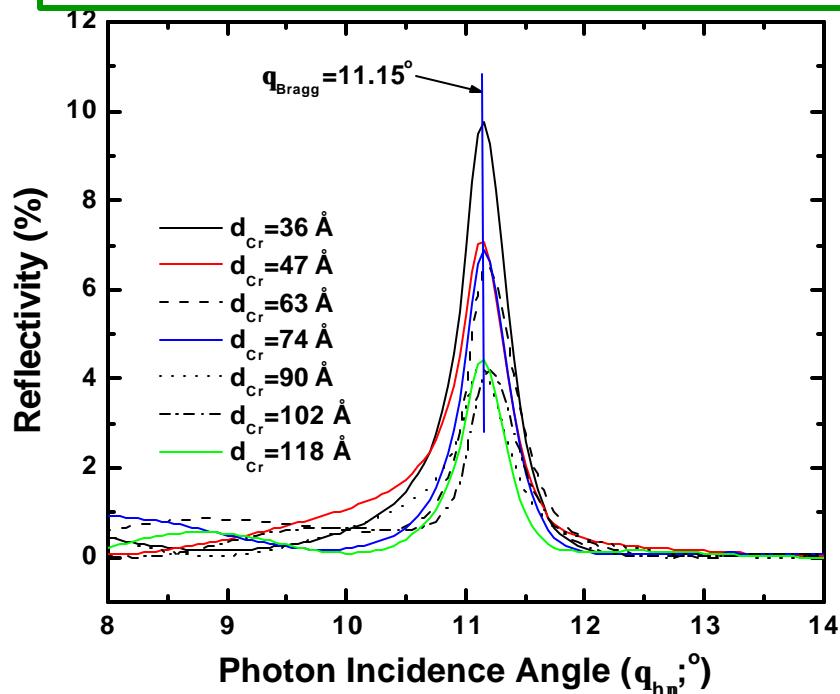


Question : How much are the standing waves affected by the bilayer Fe/Cr ?

Answer : very little (< 0.2 Å shift)

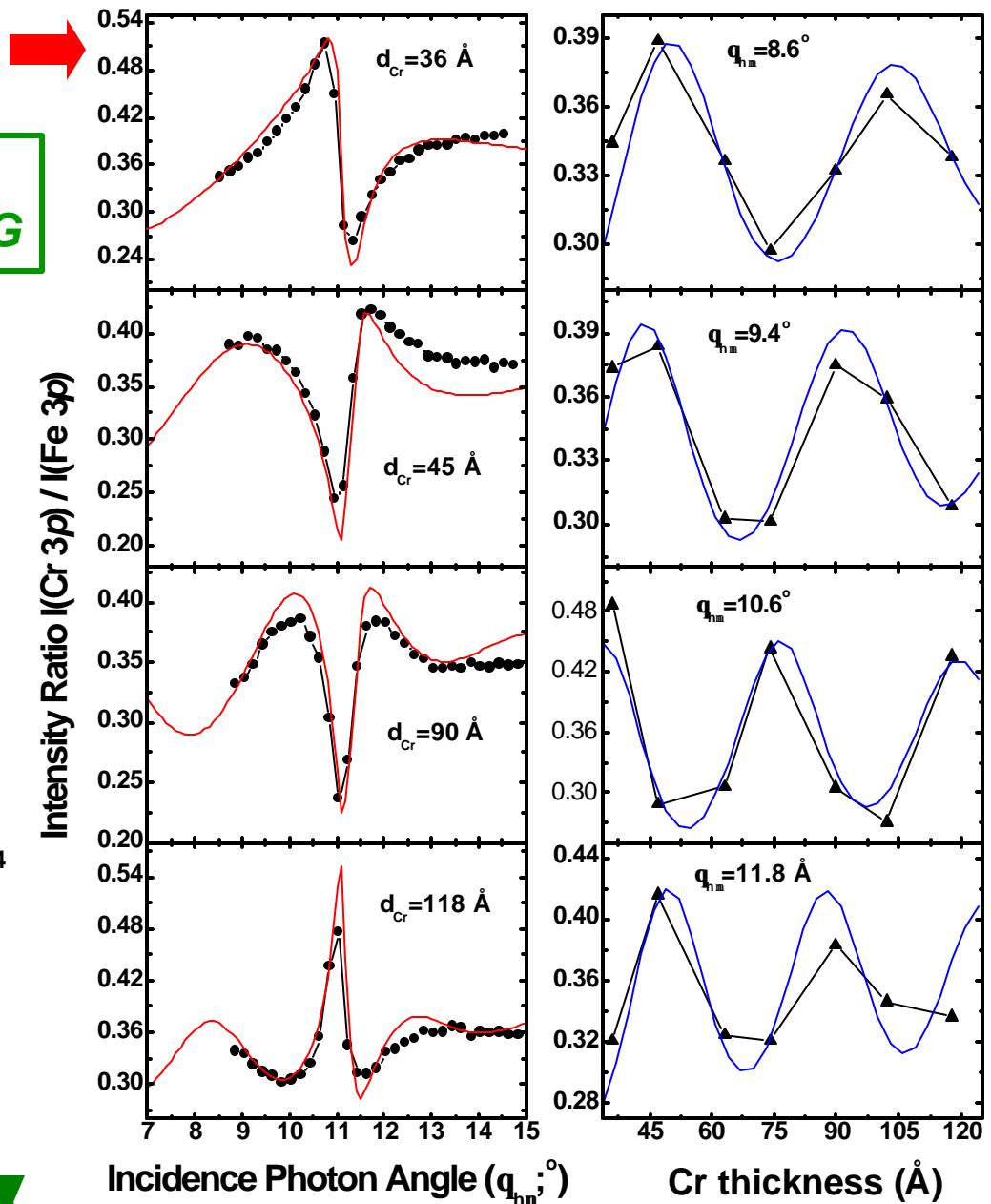
*experimental + calculated
photoemission yield ratio
 $I(\text{Fe } 3p)/I(\text{Cr } 3p)$ in (Fe/Cr)+SWG*

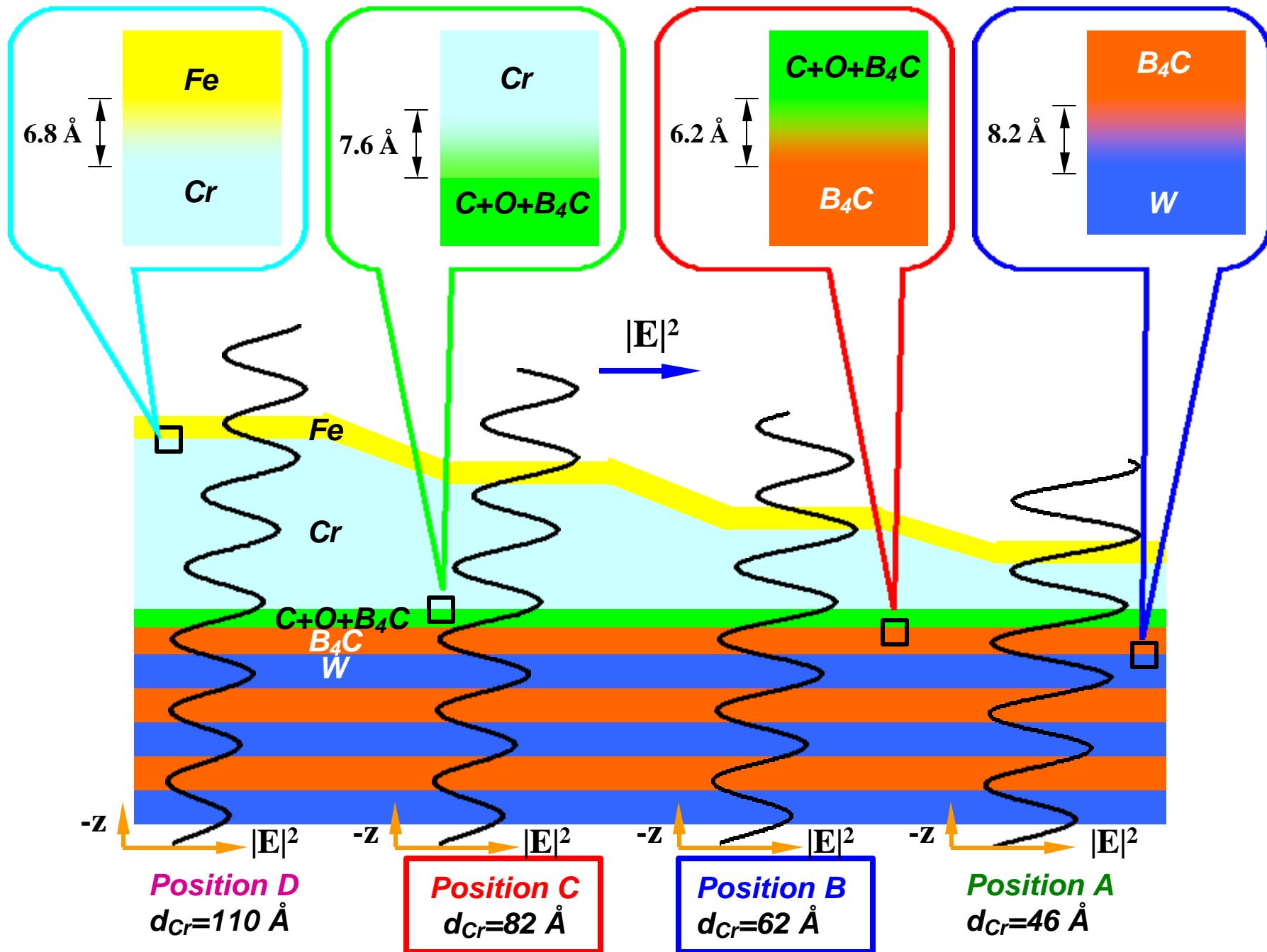
*calculated
reflectivity for wedge (Fe/Cr)+SWG*



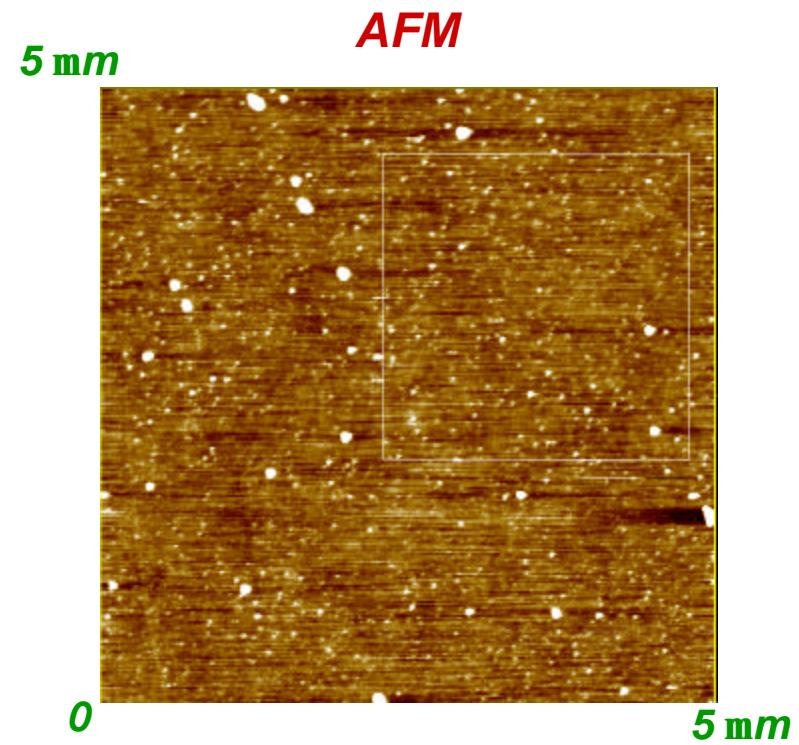
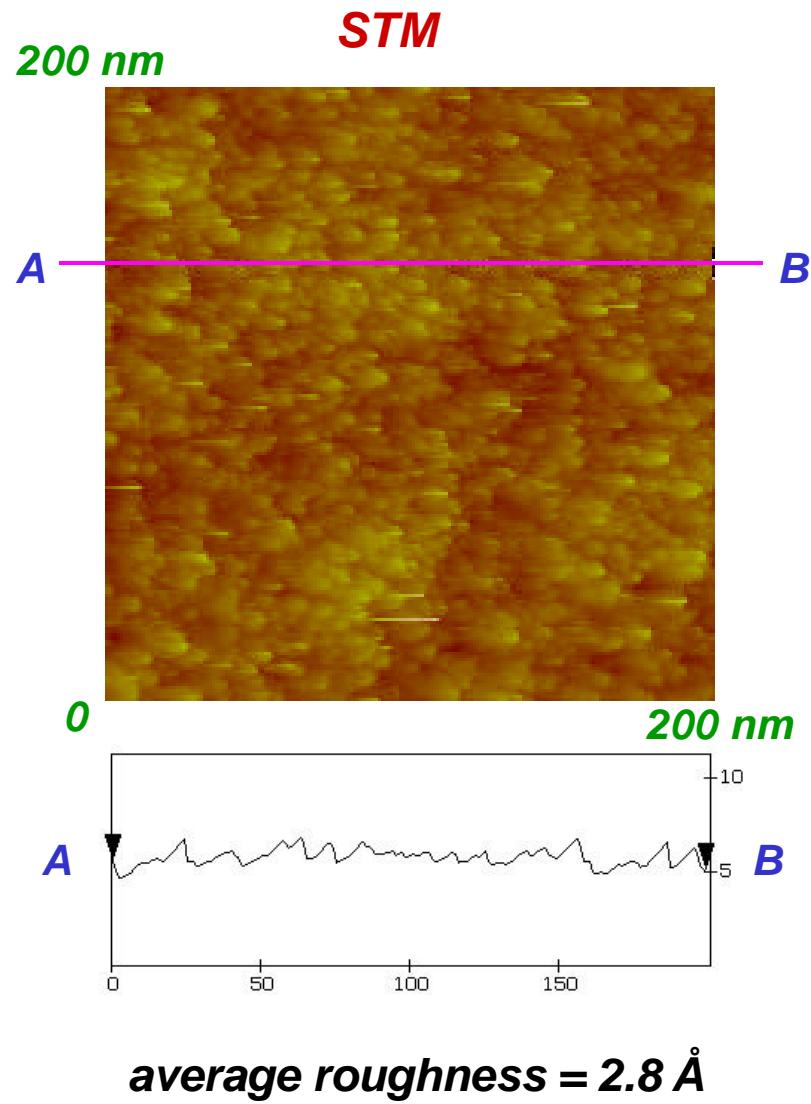
→ *calculation of q_{Bragg}
® no shift with d_{Cr}*

*"phase pinning"
of SWG vs. d_{Cr}*





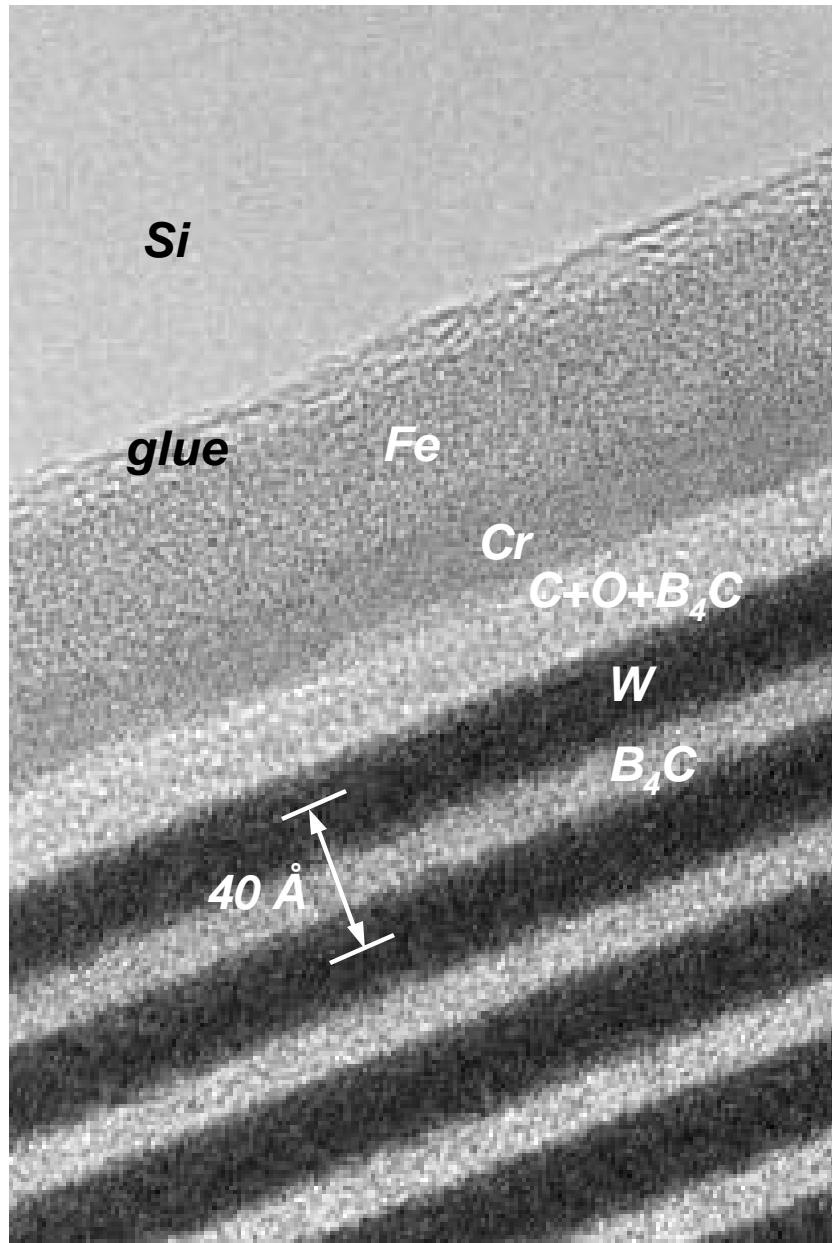
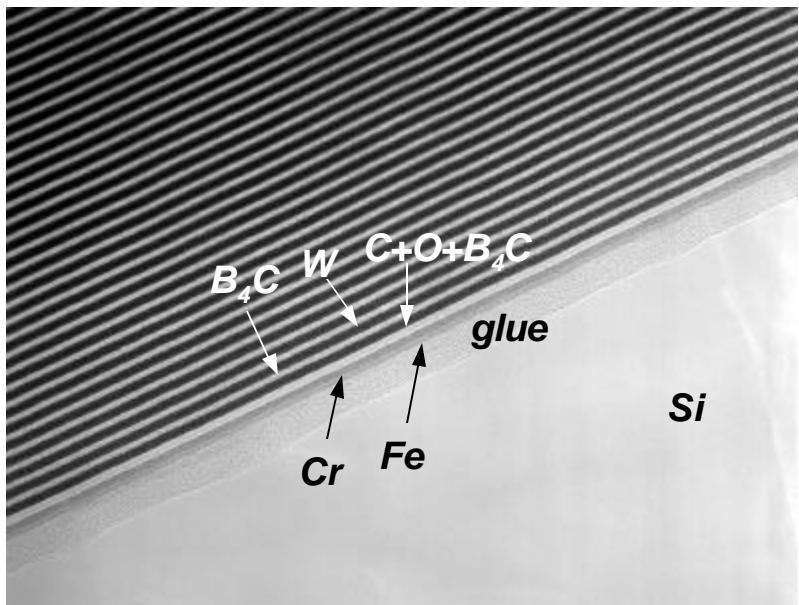
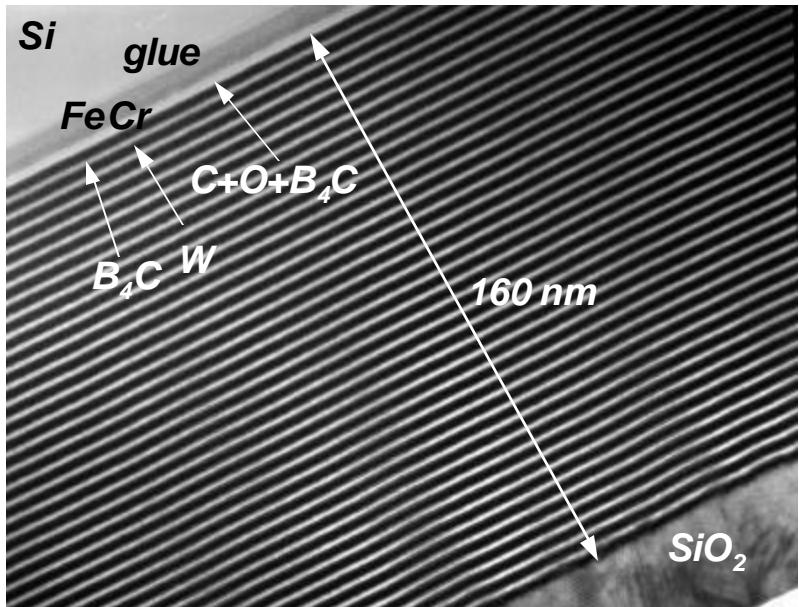
Scanning Probe Microscopy Image for Multilayer SWG

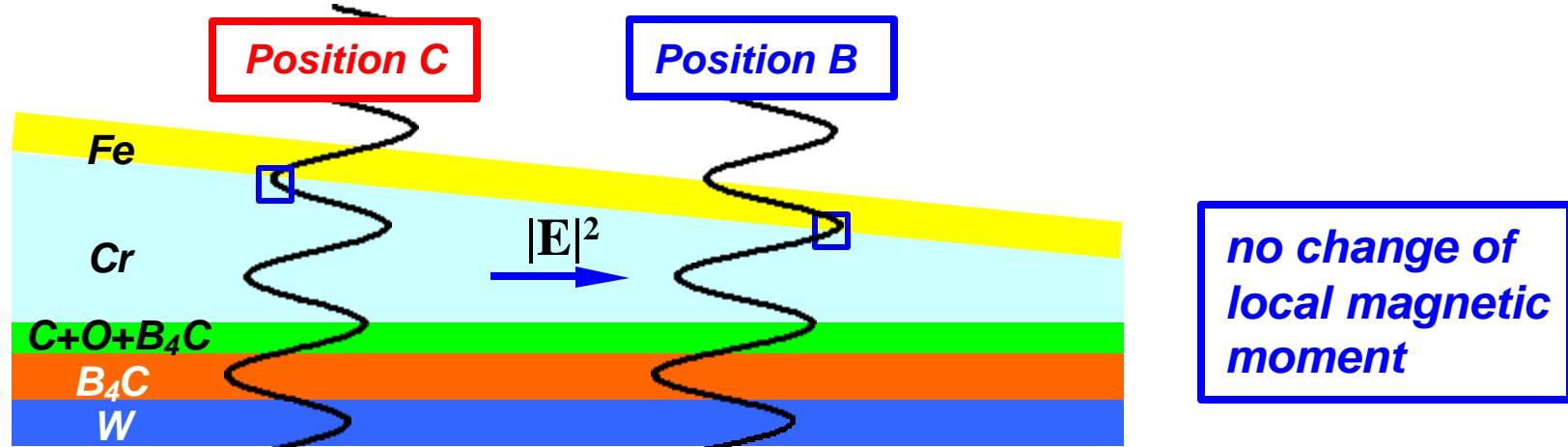


average roughness = 2.6 Å

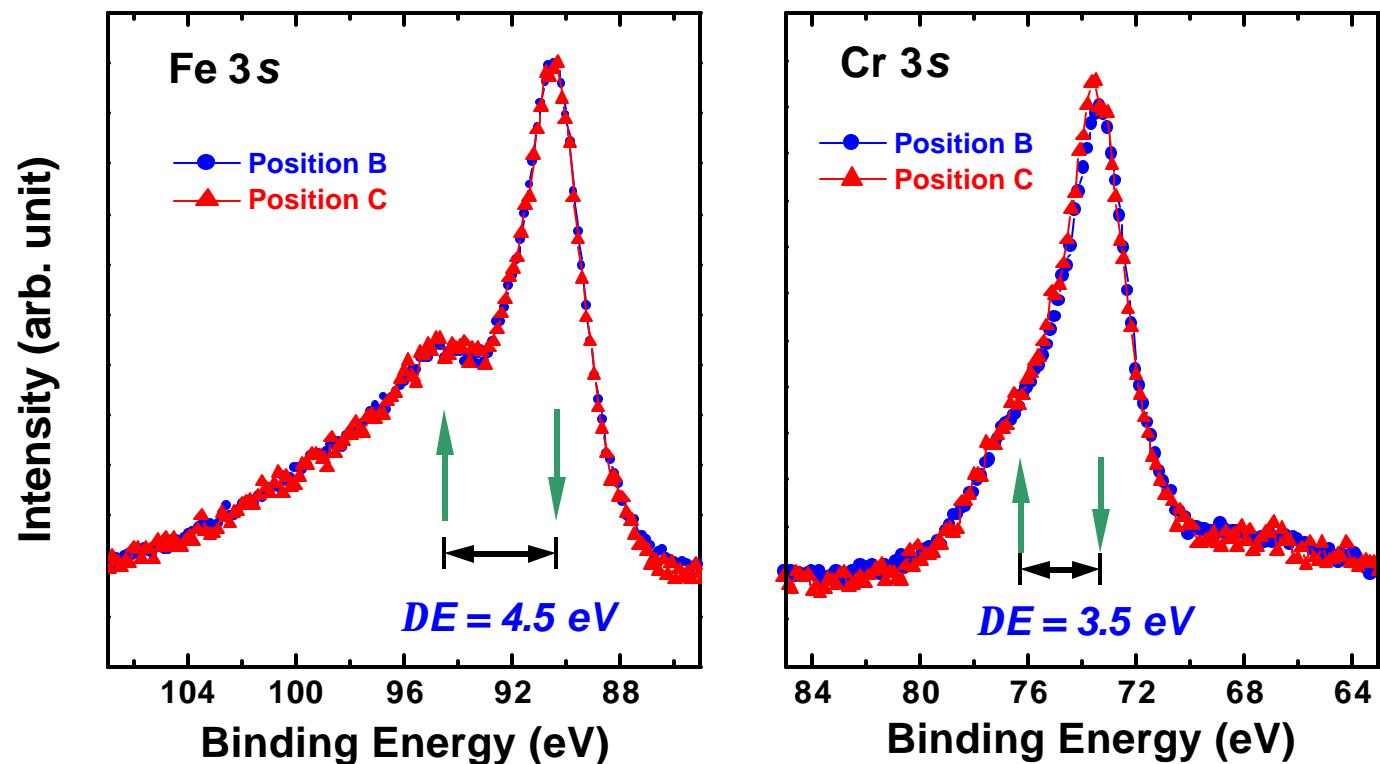
RMS roughness = 4.7 Å

Transmission Electron Microscopy Image for Fe/Cr/Multilayer SWG
(National Center for Electron Microscopy, LBNL)



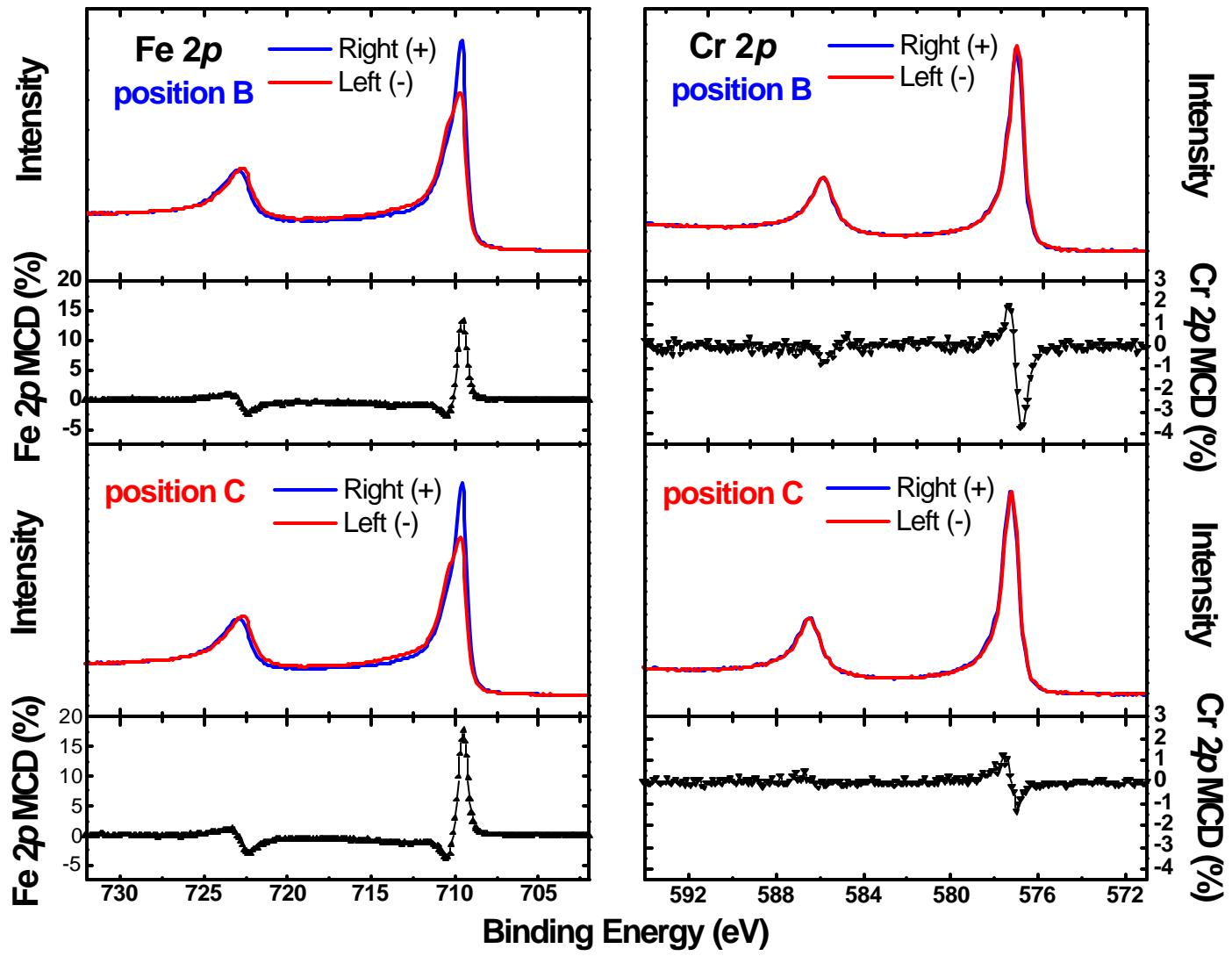
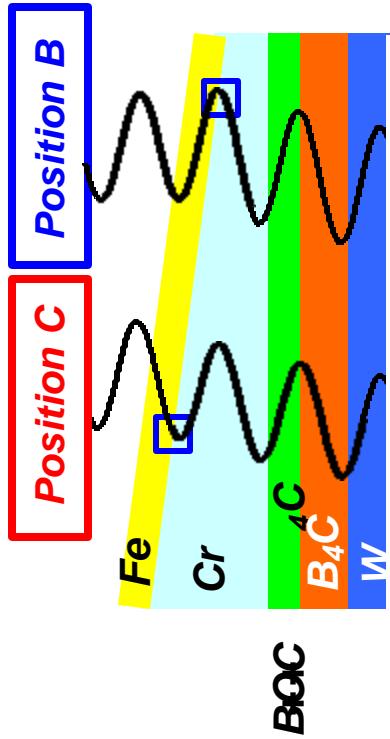


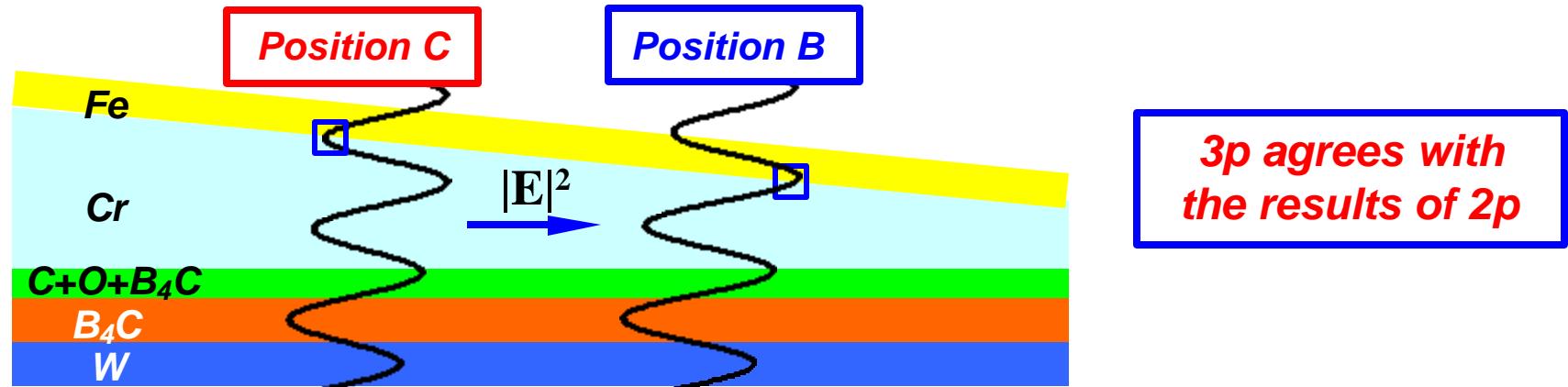
Fe and Cr 3s Photoemission in Wedge (Fe/Cr)+SWG



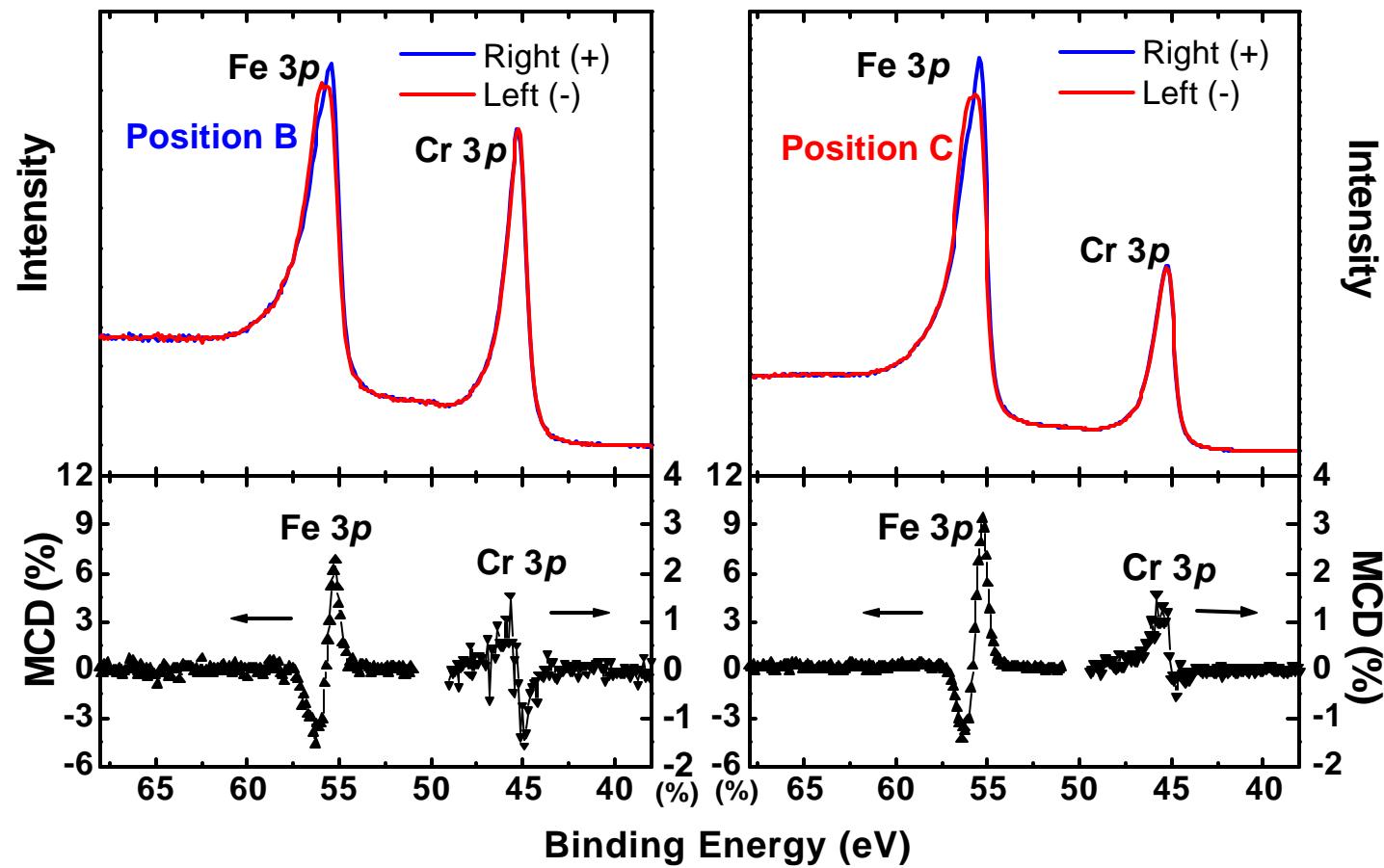
Fe & Cr 2p MCD Data for Wedge (Fe/Cr)+SWG

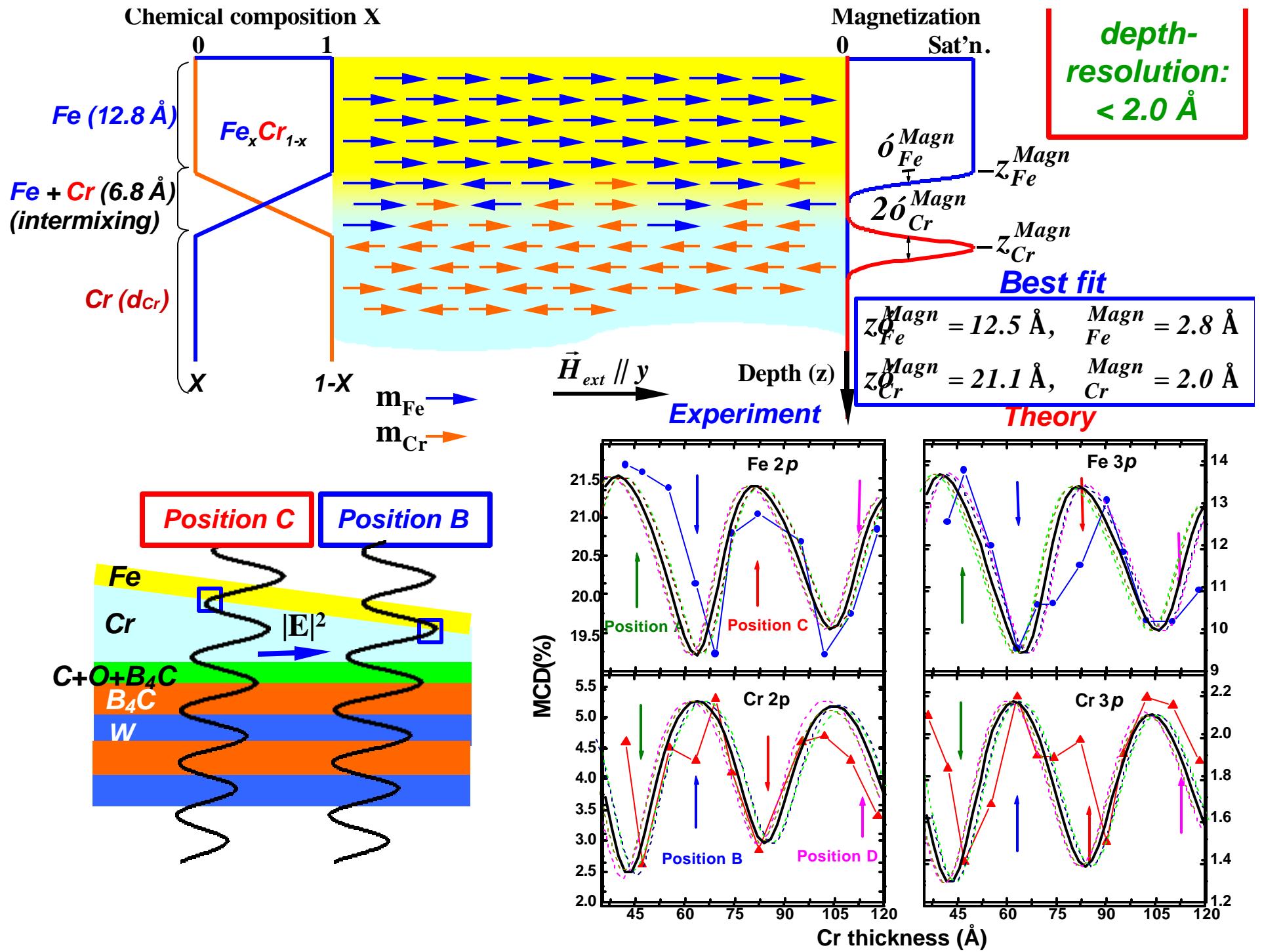
**Cr magnetization
Is antiparallel to
Fe; systematic
variation of MCD
strengths vs d_{cr}**





Fe & Cr 3p MCD Expt Data for Wedge (Fe/Cr)+SWG





Conclusion

- *depth resolved spectroscopy using multilayer standing wave generators (SWGs) promises non-destructive tool to probe buried interface in magnetic nanolayers, other nanostructures*
- $|E|^2$ at interface ~ about 40 % (min) « 160 % (max)
- *first application to Fe/Cr interface*
 - Fe, Cr : no change in magnitude of local magnetic moment
 - Fe : reduced M near interface
 - Cr : enhanced FM order near interface antiparallel to Fe M
- *future work*
 - probing surface segregation or phase separation with SWG
 - other magnetic nanostructural superlattices on SWG (e.g. exchange bias or magnetic tunneling junction)
 - nanocrystals deposited on SWGs
 - x-ray fluorescence or x-ray scattering with overlayers on SWG
 - photoelectron emission microscopy (PEEM) on SWGs

Principal Investigators, Coworkers and Collaborators



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